

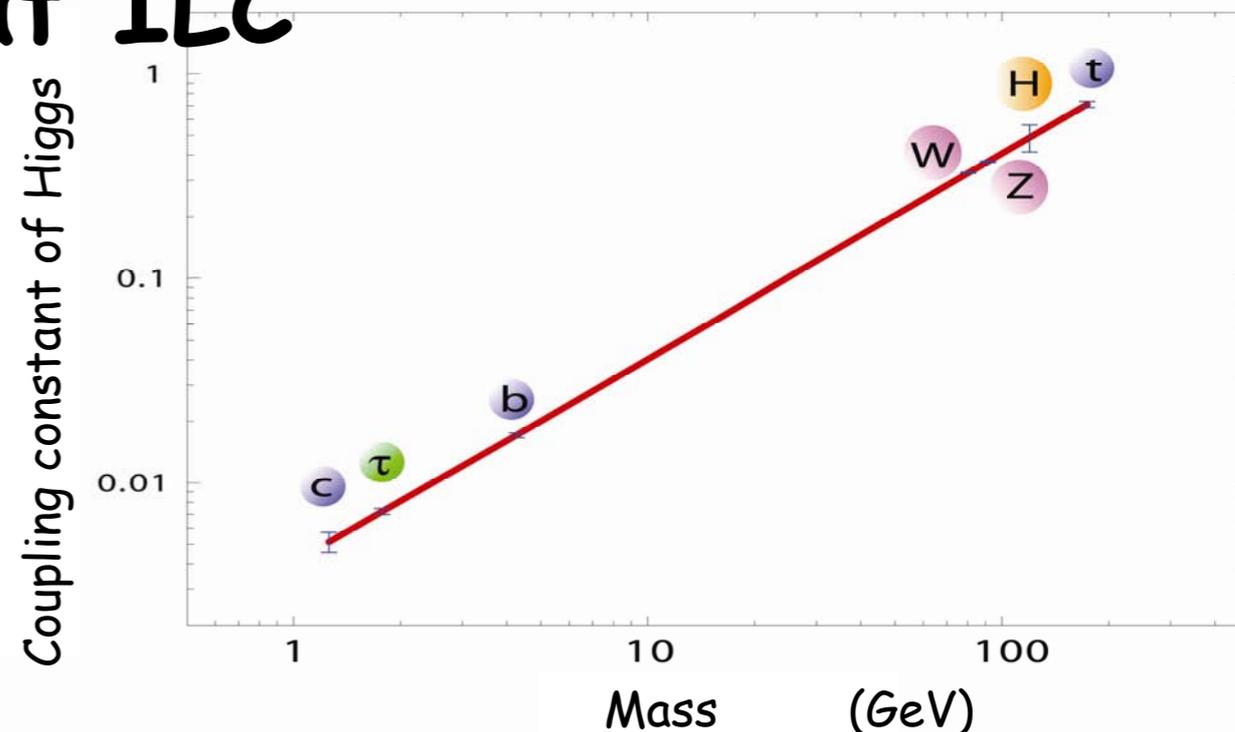
# **Asian Module for ILD-TPC**

**Akira Sugiyama(Saga)  
on behalf of LCTPC-Asia/Japan**

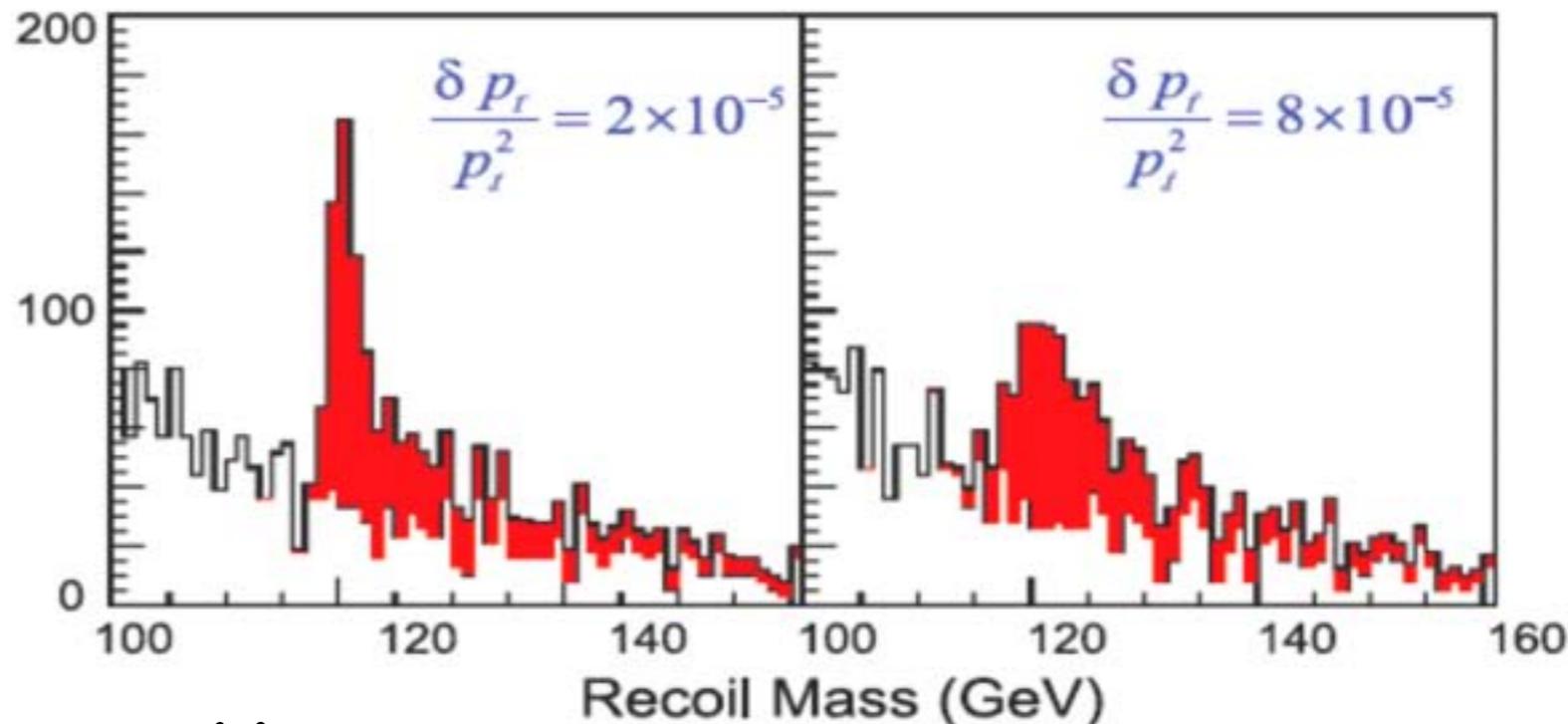
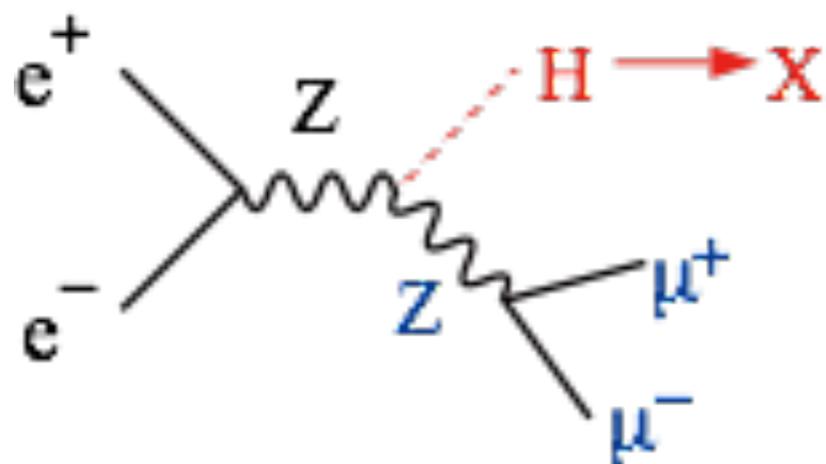
# Requirements to Tracker at ILC

Good momentum resolution

Coupling-Mass Relation



$$M_X^2 = (p_{CM} - (p_{\mu^+} + p_{\mu^-}))^2$$



Missing mass resolution @ higgs Strahlung process

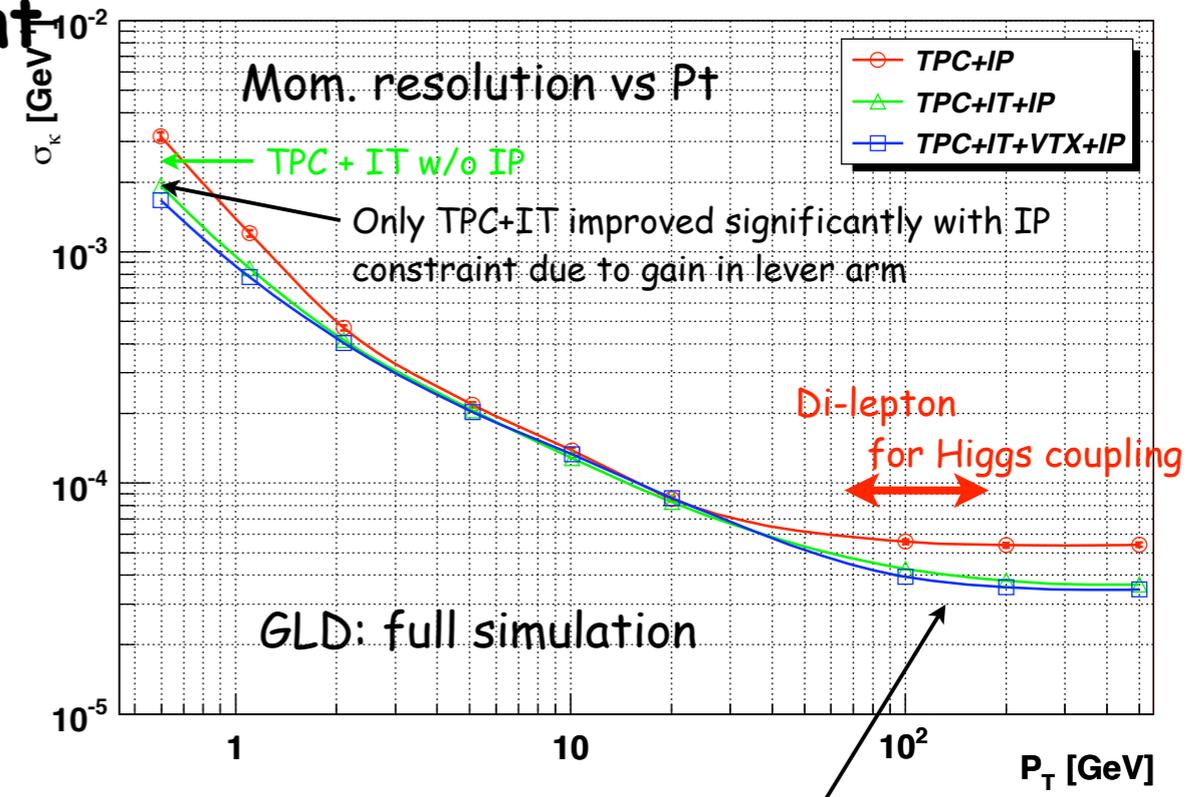
bias free Higgs decay study

$$dP/P \sim 10^{-5} P$$

10 times better resolution than that of LEP TPC

# TPC w/ Vtx can satisfy the requirement

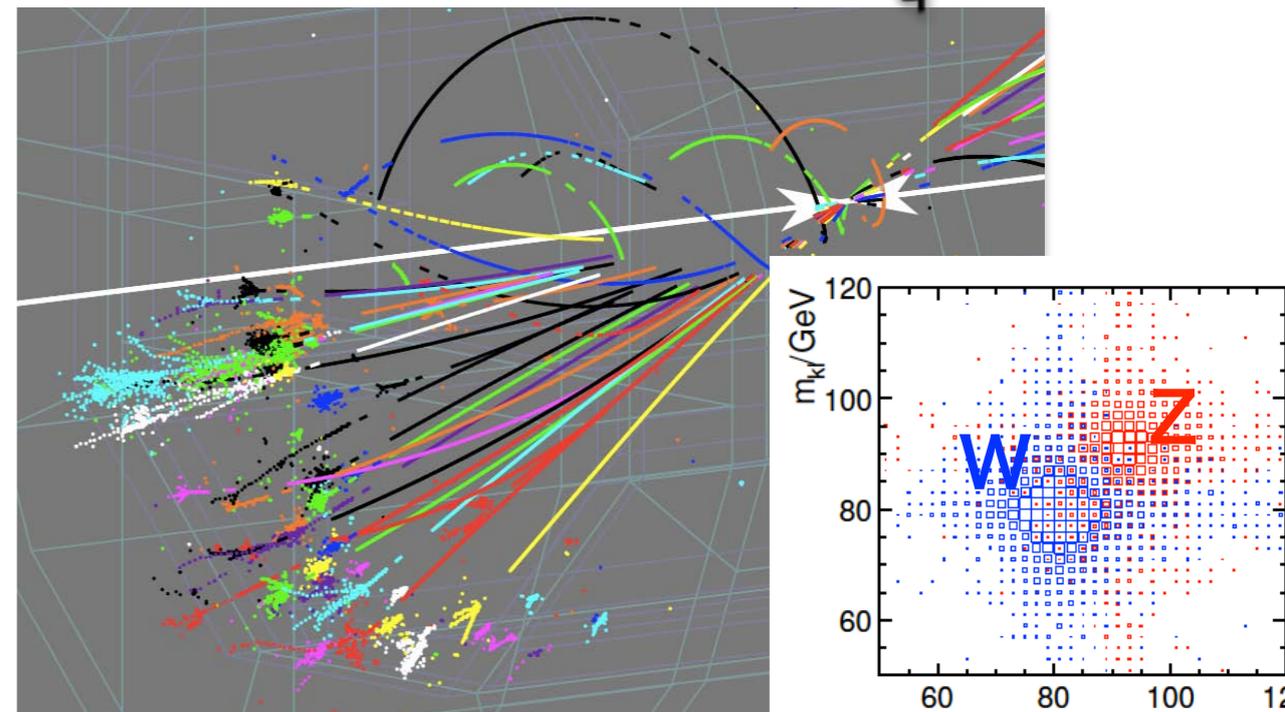
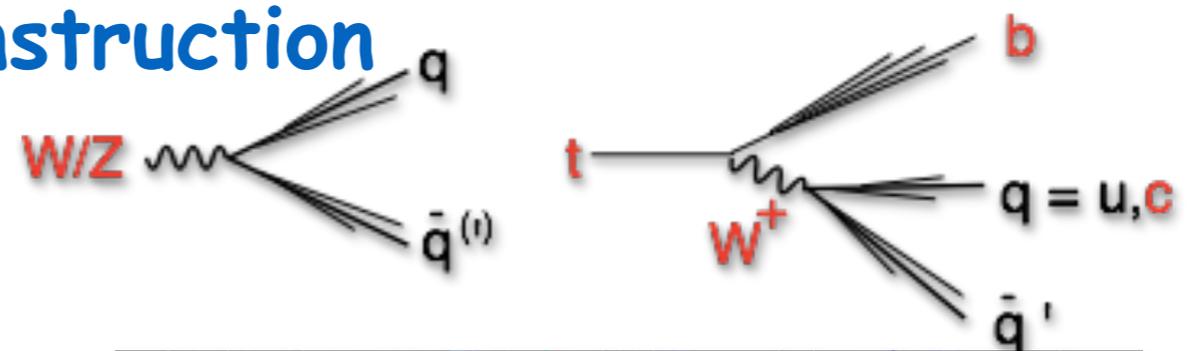
Tracking efficiency is another important issue for Jet Energy resolution (ie. Particle Flow Algorithm)



## Good efficiency for track reconstruction

Particle Flow Analysis(PFA) allow us to separate Z and W in Jet Mass energy

cluster-track matching is essential



# ILD 測定器

カロリ  
メータ

飛跡

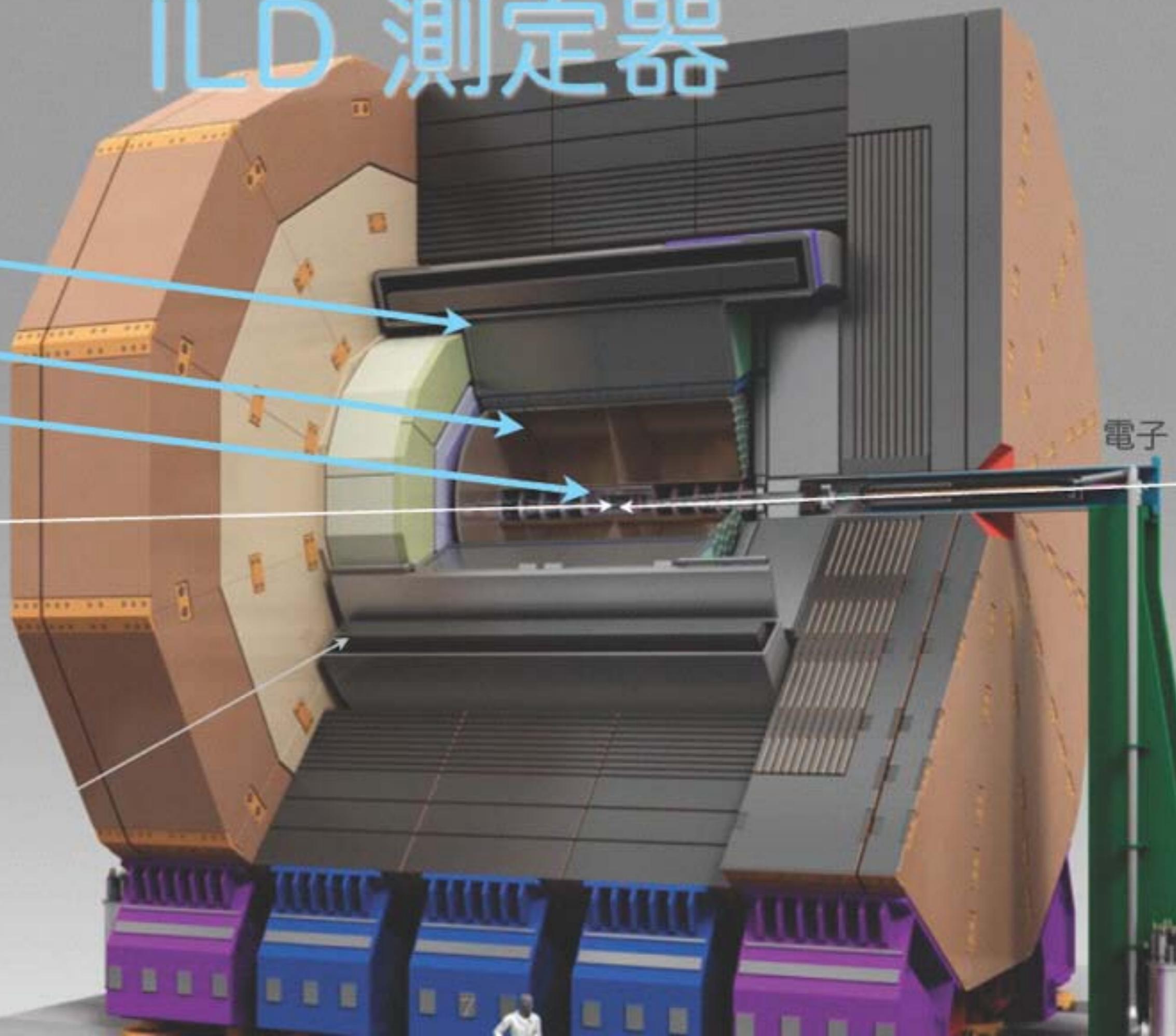
VTX

陽電子

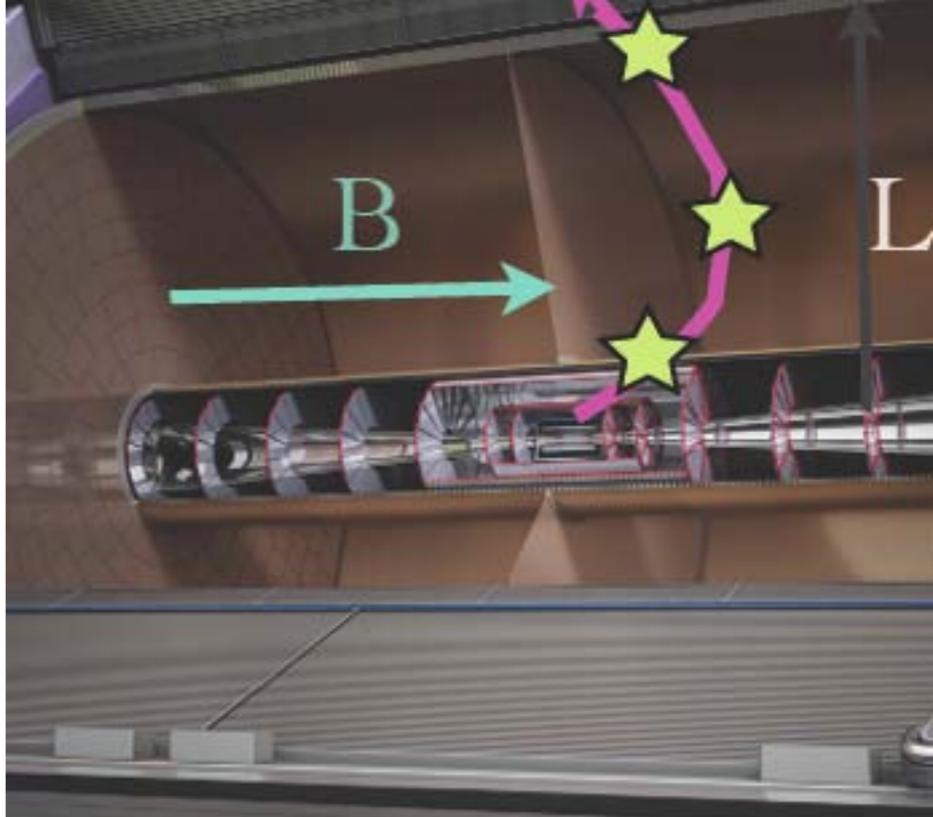
電子

磁場用

コイル



# Possible solution of ILD Tracker



	posi. reso	# meas. point
Si pixel VTX	$\delta \sim 5\mu\text{m}$	6
Inner Si strip	$\delta \sim 20\mu\text{m}$	6
TPC main tracker	$\delta \sim 100\mu\text{m}$	220
( Si main tracker	$\delta \sim 20\mu\text{m}$	5 )

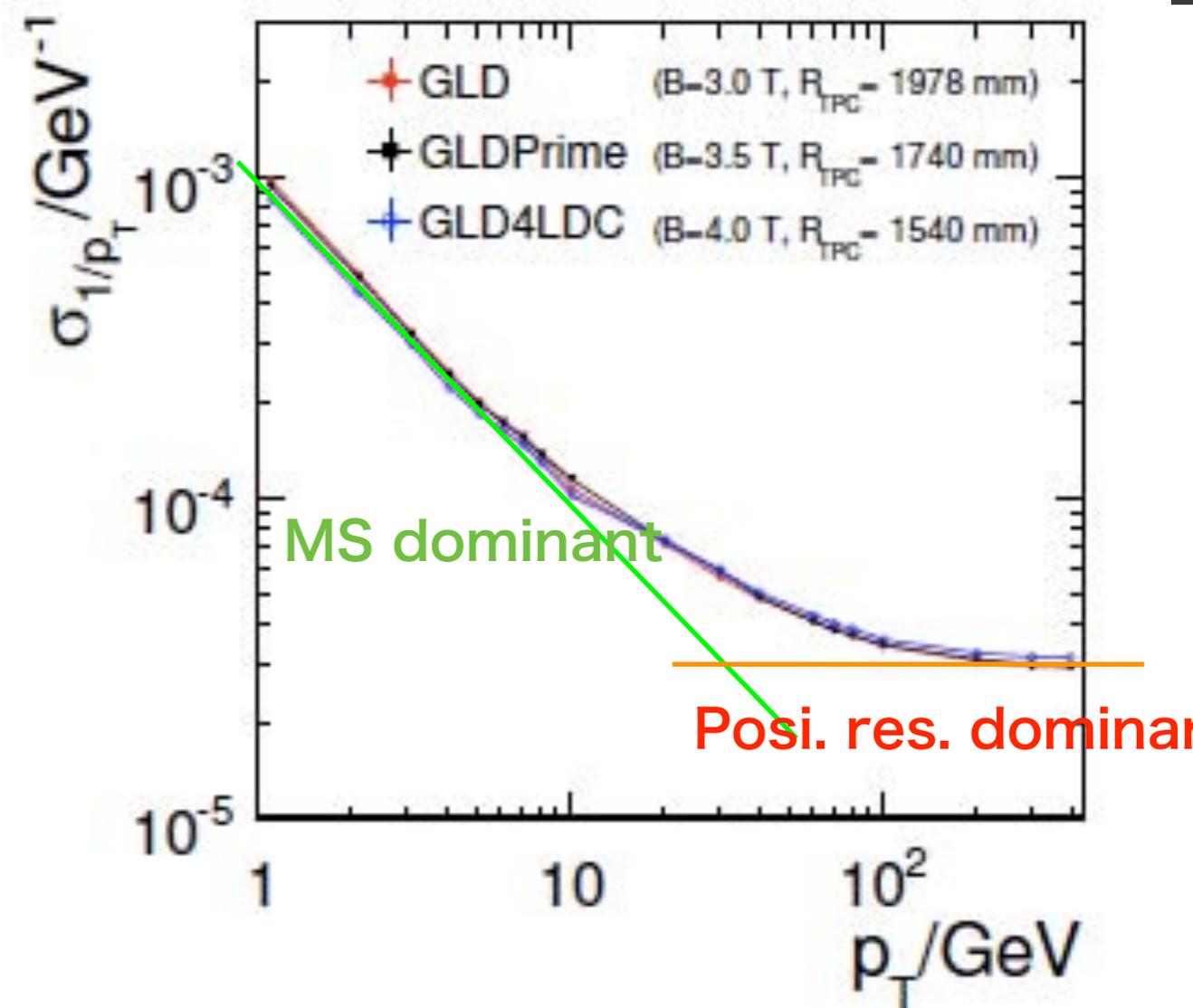
## Momentum resolution

position resolution  $\left(\frac{\delta p_T}{p_T}\right)_{meas.} = \frac{3.3\sigma_{r\phi} p_T}{BL^2} \sqrt{\frac{720}{n+4}}$

multiple scattering  $\delta P_{T(M.S.)} = \frac{0.016P}{0.3BL\beta} \sqrt{\frac{L}{X_0}}$

## MS term limits # of Si layer

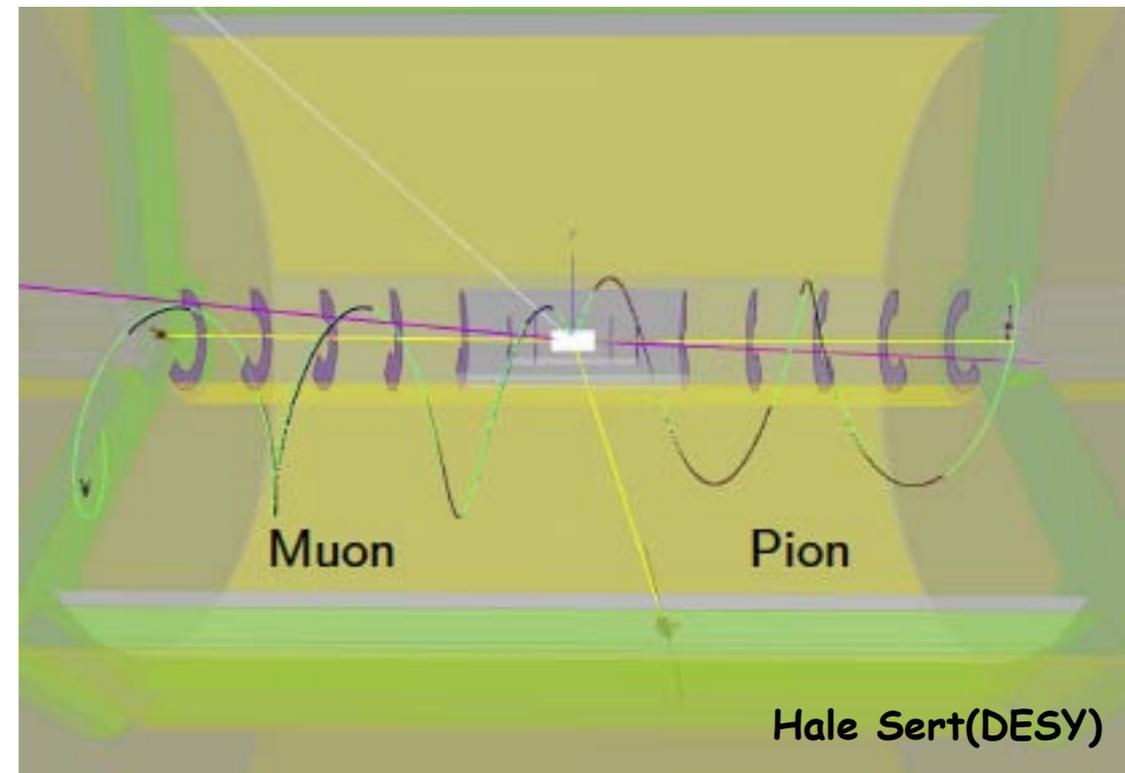
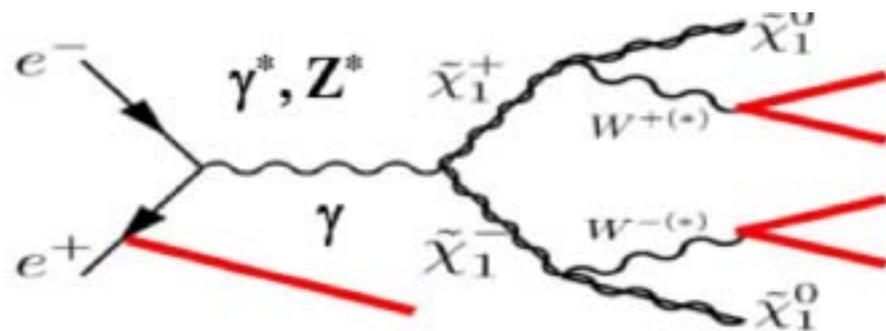
->  $\sigma/\sqrt{n}$  is same for TPC and Si tracker  
( if B, L are same )



# Gaseous tracker

TPC : continuous tracking = many sampling of moderate precision  
good tracking efficiency

degenerate Higgsino case: only low Pt  $\pi/\mu$  tracks



# Si tracker

small sampling but with high precision

tracking efficiency ??

good for high Pt track

but not sure for low Pt track

# Requirements to TPC

momentum resolution

**local resolution** : 100um over full drift volume

no distortion ( E-field, B-field )

B-field: anti-DID recon. under non-uniform B-field

E-field: geometrical/engineering

beam related **ion problem**

detection efficiency

stable operation of gas amplification

good 2track separation

good efficiency even in high BKG

less material

structure

RO electronics/cooling

# The way to achieve local resolution 100um

$$\sigma_{\kappa} = \delta \left( \frac{1}{P_T} \right) = \frac{\sigma_x}{0.3BL^2} \sqrt{\frac{720}{n+4}}$$

High B field	3.5 T
Long lever arm	1.8 m
Many hits	200 layers

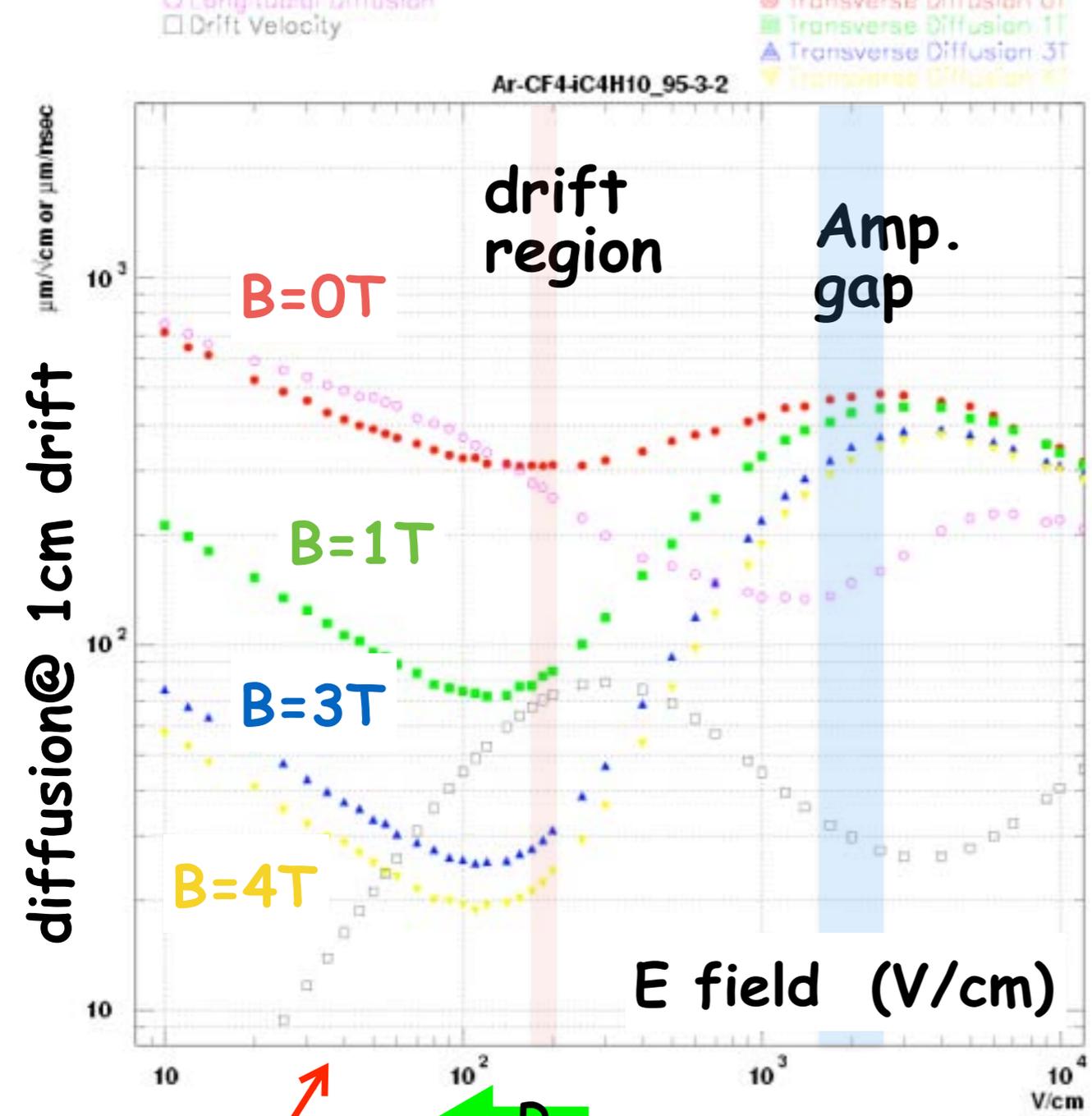
good position resolution	100 um
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**principle of gas detector**

**property of gas**

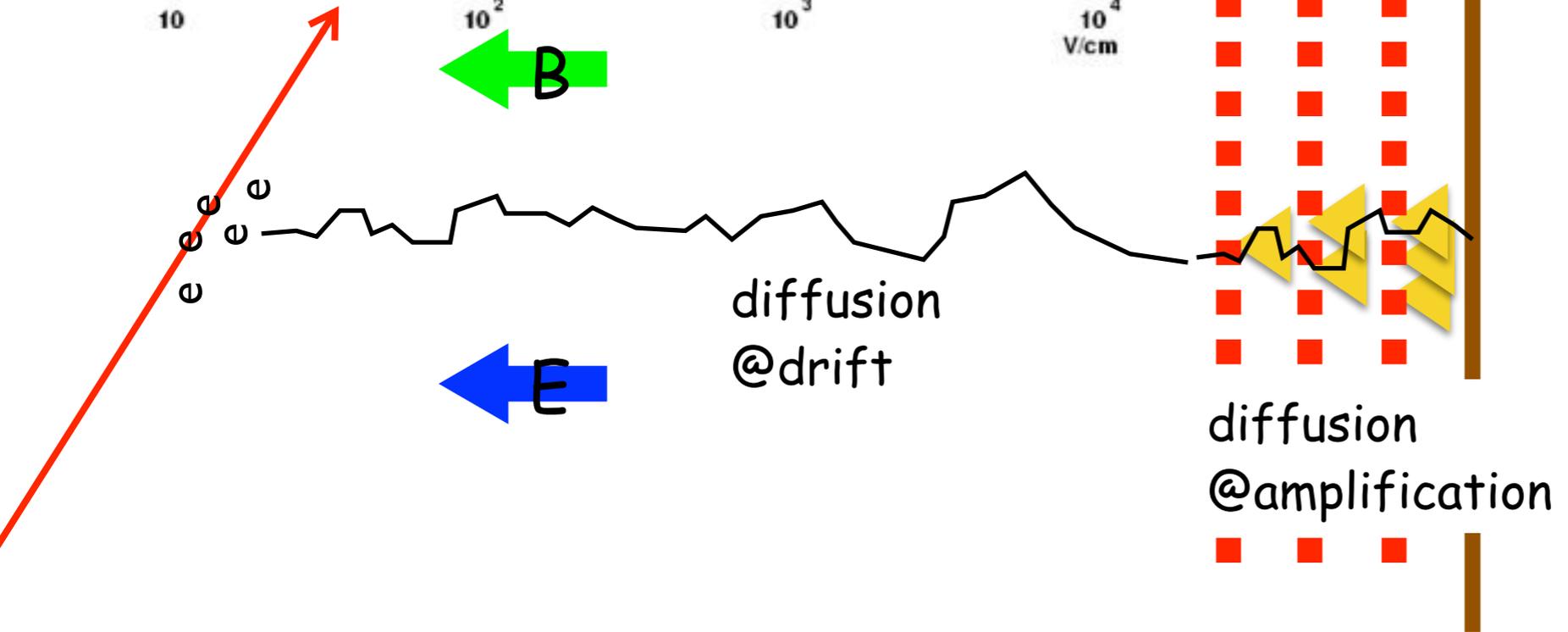
**principle of position measurement**





Gas property  
 Ar:CF4:i-C4H10  
 high wt

3.5T case  
 CD ~ 25  $\mu\text{m}$ @1cm drift at drift region  
 350  $\mu\text{m}$  at amp. region



less diffusion@drift  
 Position information is smeared by diffusion



modest diffusion@amp.  
 COG of charge dist.  
 Charge distribution must be broader than RO pad.

# Position accuracy of single electron

If RO pad is enough narrow

$$\sigma_x = C_D \sqrt{z}$$

@2 m drift

-> 350  $\mu\text{m}$

If RO pad is too wide

$$\sigma_x = \sqrt{(C_D \sqrt{z})^2 + \frac{w^2}{12}}$$

hose-scope effect is accumulated

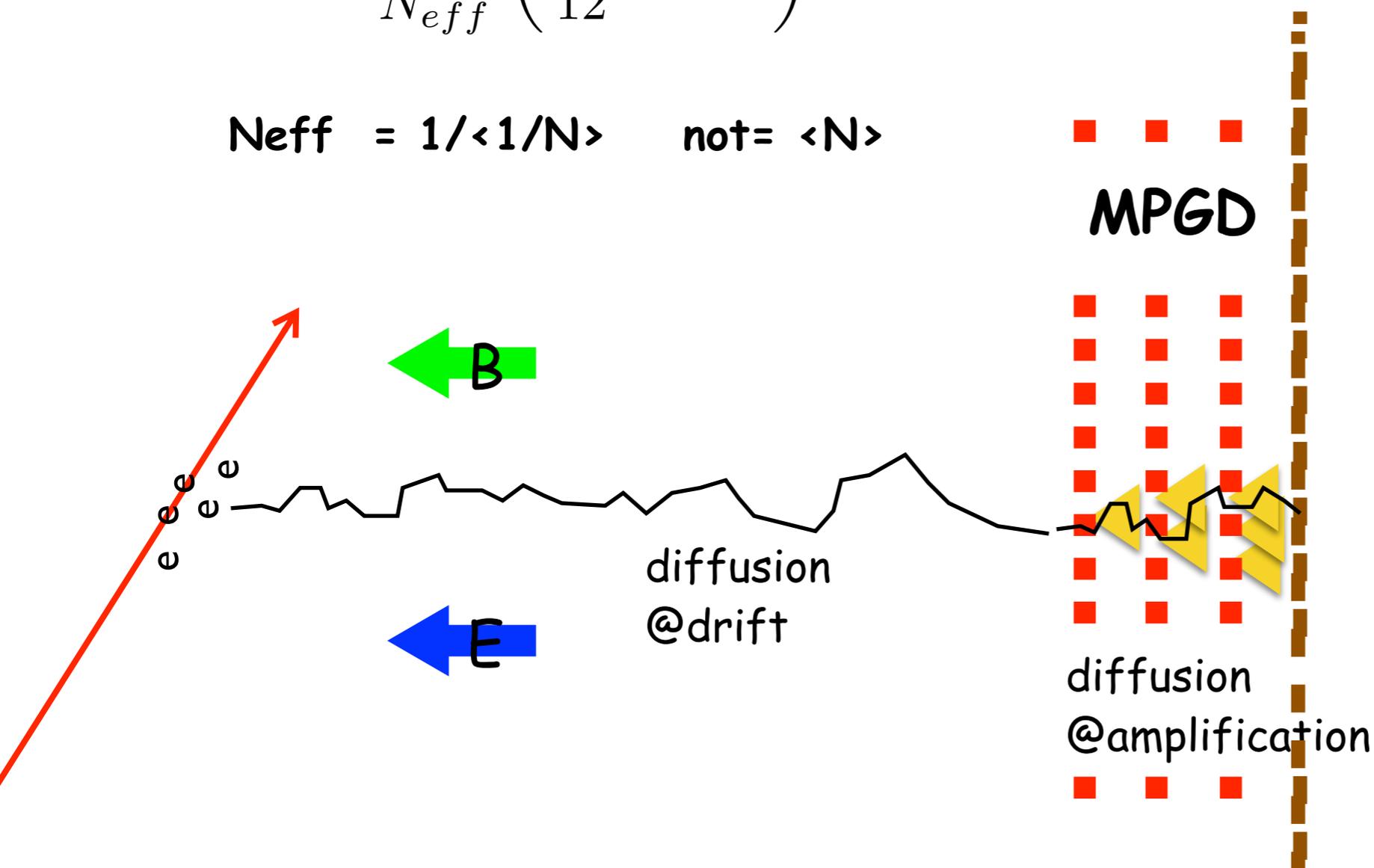
Hose-Scope effect may disappear

if  $w < 3 * \text{diffusion@amp.}$

# Position accuracy of electron cluster

$$\sigma_x^2 \sim \frac{1}{N_{eff}} \left( \frac{w^2}{12} + C_d^2 z \right)$$

$N_{eff} = 1 / \langle 1/N \rangle$  not =  $\langle N \rangle$

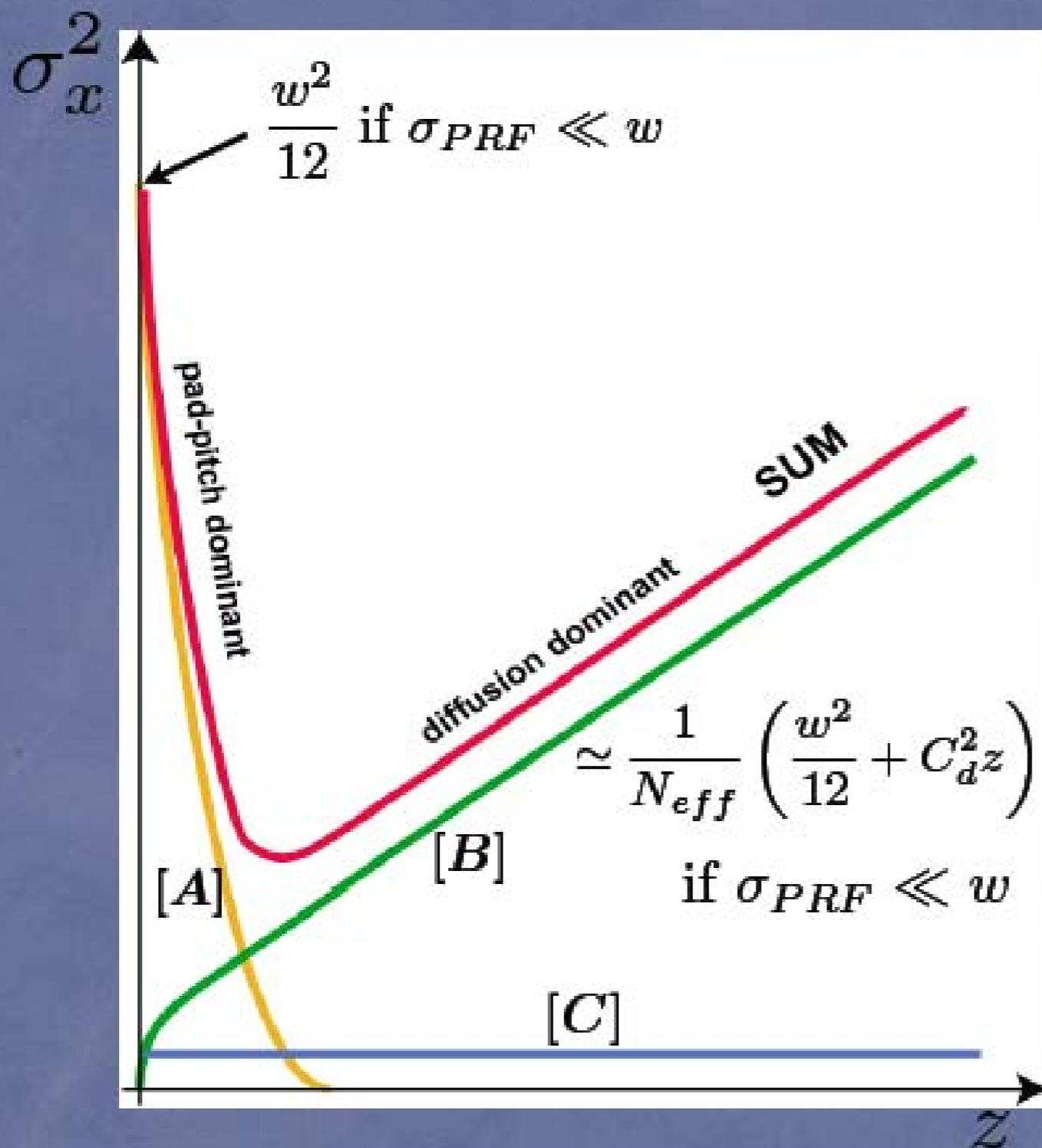


diffusion@amp.  $\sim 300 \mu\text{m}$   
dep. on gap



pad width = 1mm  
is reasonable  
for GEM case

# Interpretation



[A] Purely geometric term (S-shape systematics from finite pad pitch): rapidly disappears as  $Z$  increases

[B] Diffusion, gas gain fluctuation & finite pad pitch term: scales as  $1/N_{eff}$ , for delta-function like PRF asymptotically:

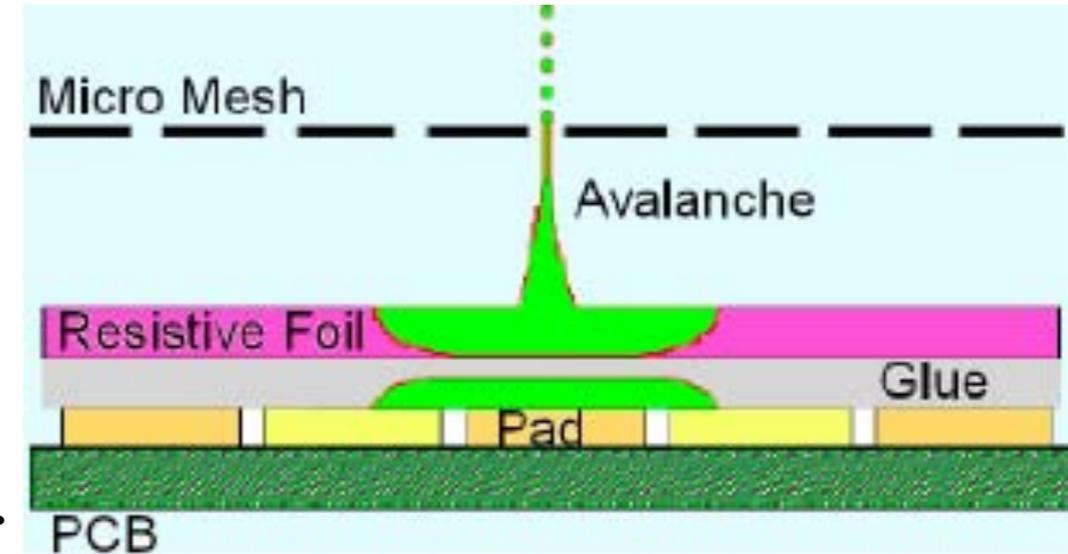
$$\sigma_{\bar{x}}^2 \approx \frac{1}{N_{eff}} \left( \frac{w^2}{12} + C_d^2 z \right)$$

[C] Electronic noise term:  $Z$ -independent, scales as  $\langle 1/N^2 \rangle$

# Alternative solution

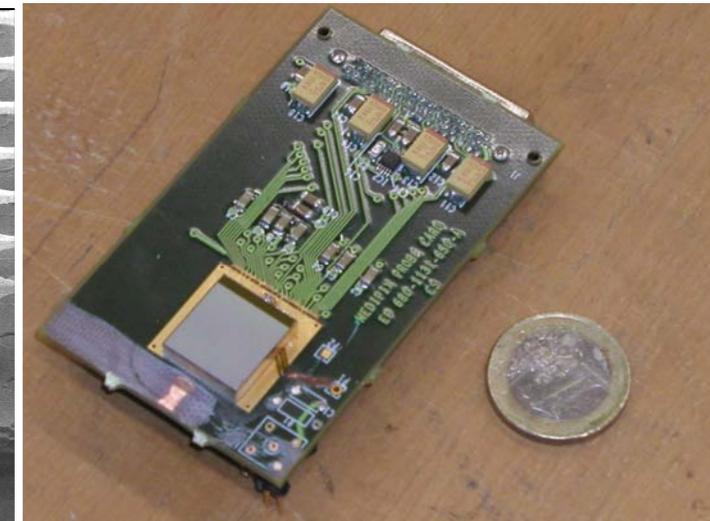
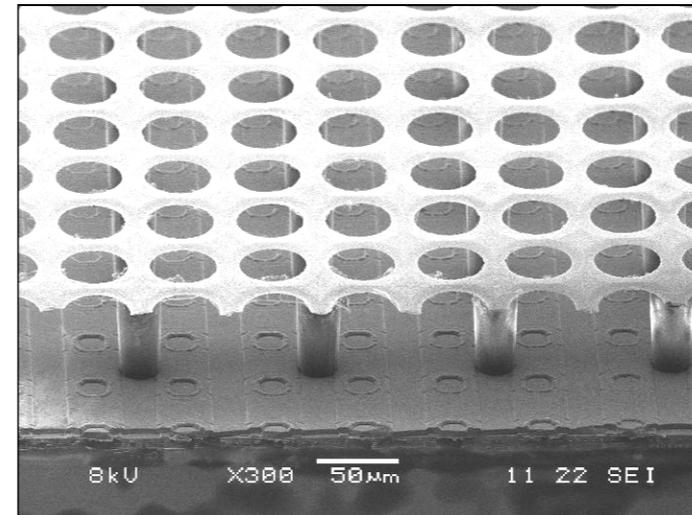
## Micromegas :

diff@amp. region is only 10~20  $\mu\text{m}$   
In order to avoid hode-scope effect  
micromegas choose resistive anode pad plane.



## Timepix w/ micromegas :

narrow pad size  $55\mu\text{m} \times 55\mu\text{m}$   
hode-scope effect is small enough  
count each electron not cluster



## MWPC :

cannot provide good resolution at high B field

# Ion problem

Production of Ions is inevitable in gas detector.

dense ions in drift volume may deteriorate drifting electron.

## Primary ions : produced by generated charged tracks

### Background @ ILC

#### mini-jets

$2 \times 10^4$  tracks/train  $\sim 10$  tracks/bunch  
 $\sim O(0.3\%)$  occupancy @ innermost raw( $r=45\text{cm}$ )  
*naive estimation*

low Pt tracks contribute more(curling)

these rates are dep. on BDS/IR design

GAS in TPC (H less gas ?)

### Physics background

2 photon process - mini jets

### Beam background

pair background

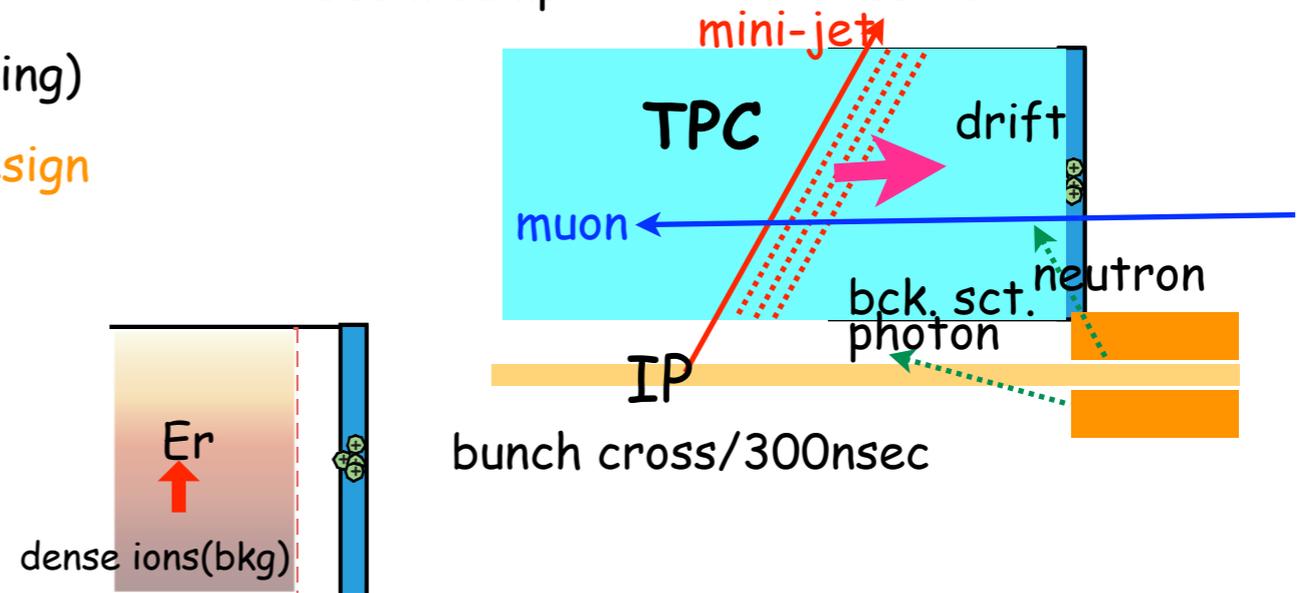
disrupted beam

beam dump

photon, electrons

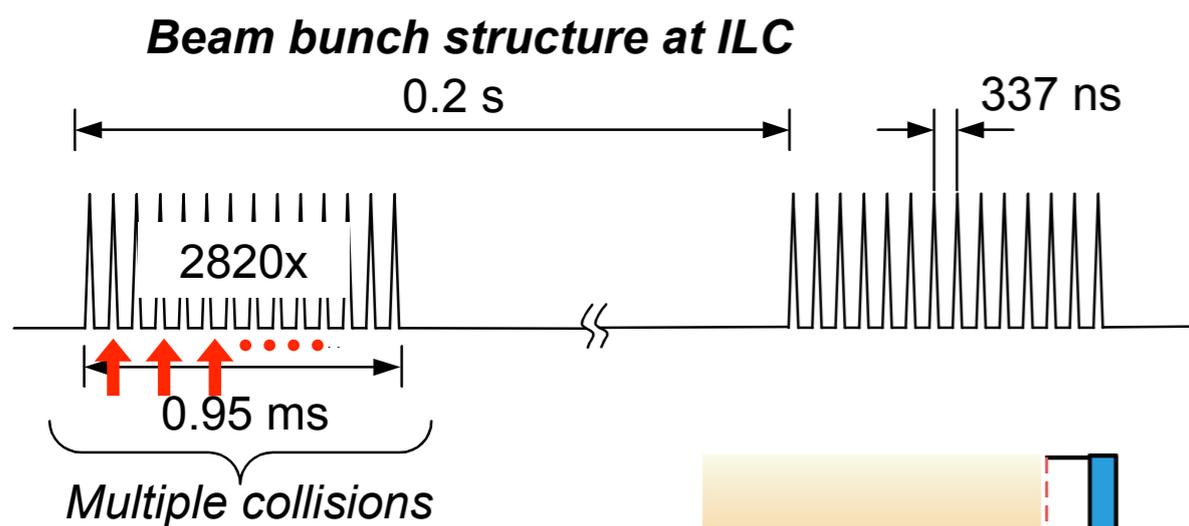
muon

neutron



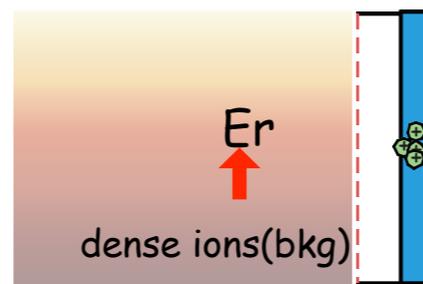
ions from gas amplification(backdrift ions) :  
 ions (dense) discs are formed due to slow drift velocity  
 MPGD owns inherent ability of ion absorption

## Beam Structure @ ILC

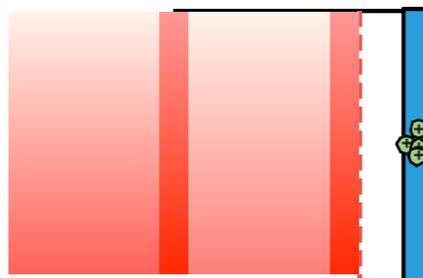


train produce back-drift ions' disk  
 without "Gate mechanism" for ions  
 as big difference of drift velocity  
 between electron and ion  
 drift velocity of ion is 10000 times slower

1st train produce prim. ion pairs in all drift volume  
 electron drift to MPGD(endplate)  
 and amplification produce more ions



next train produce prim. ion pairs again  
 before ions are swept out  
 amp. ions by 1 train form thin disc and drift slowly



is a natural ability of  
 s, but it's not perfect.

"GATE"ing GRID

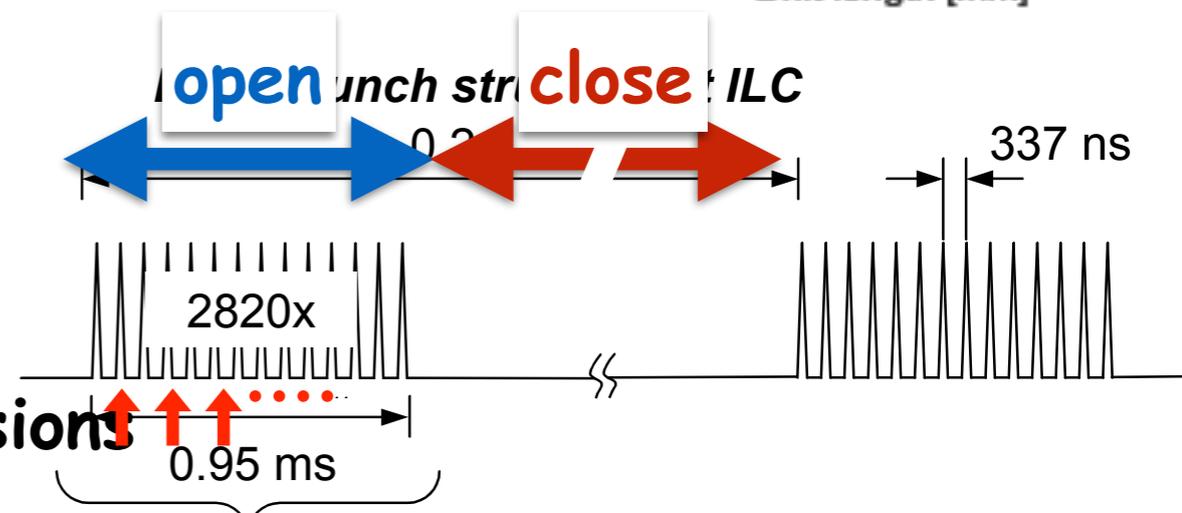
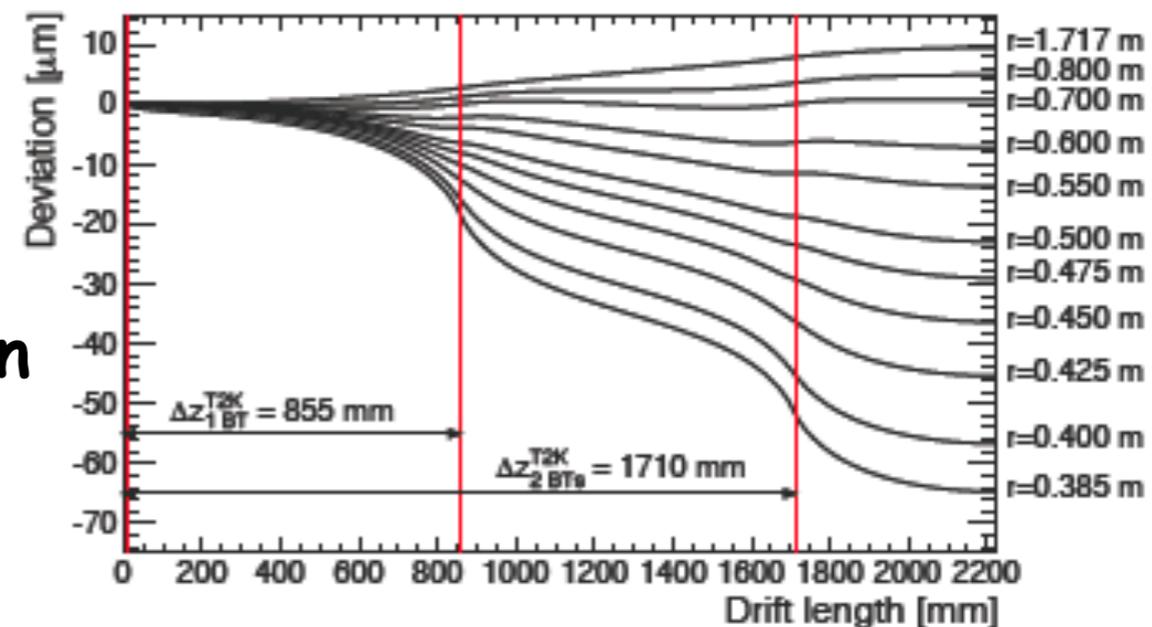
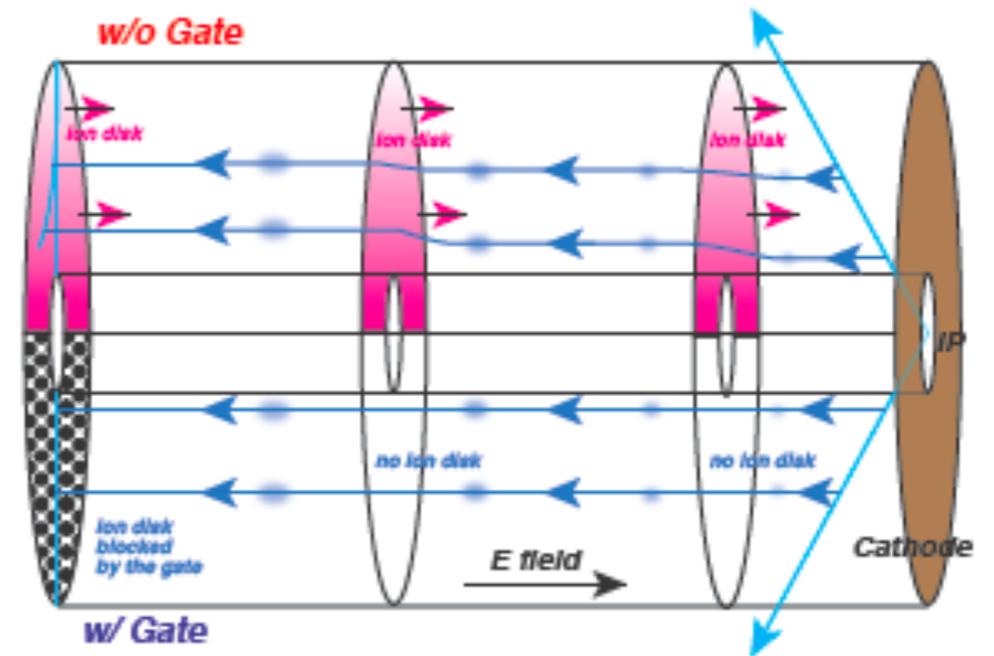
# Effect of ion (disc)

Primary ions are inevitable  
 no way to recover  
 but ions are spread over all volume  
 effect to position measurement is  
 acceptable  $O(10 \text{ } \mu\text{m})$

Ions produced by amplification form  
 dense ion disc which deteriorate  
 position accuracy  $\sim 60 \text{ } \mu\text{m}$   
 not negligible to 100  $\mu\text{m}$  resolution

**We need Ion Gate device**

ILC beam structure is good for gating  
 gate is open for 1ms collision  
 gate is closed for 199ms between collisions



# Gating for back-drift ions

ILC case : ions feedback must be smaller than  $10^{-3}$  (ie. no ions from MPGD)

Gate can be open for **1 msec** and be closed following **199 msec**.

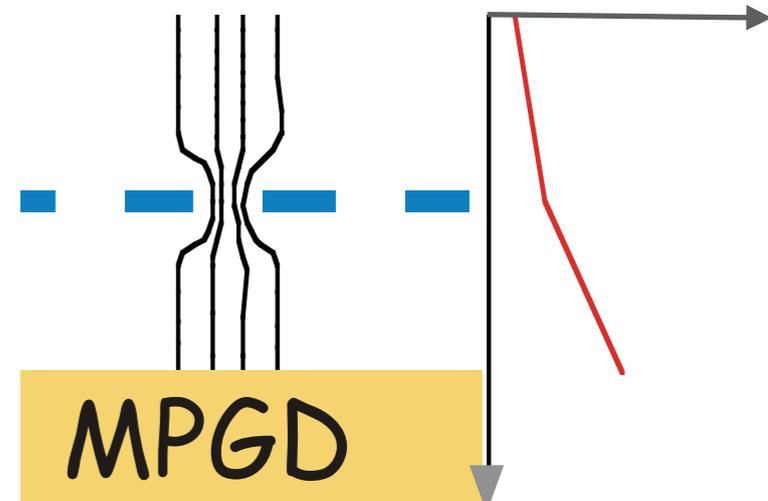
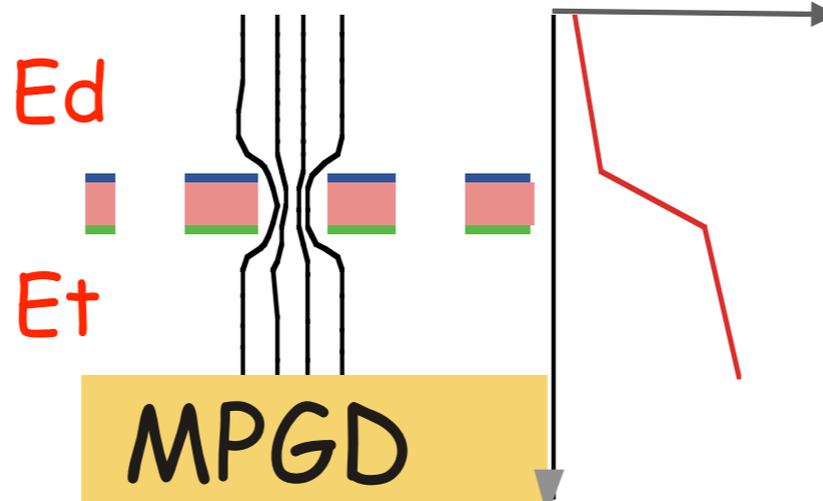
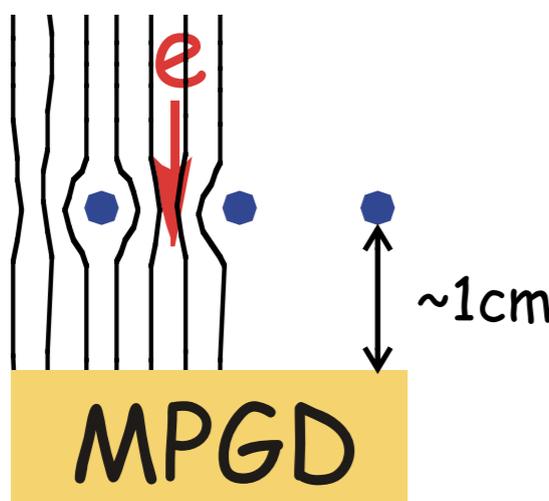
ion can drift  $< 1\text{cm}$

Gate: wire  
3 candidates

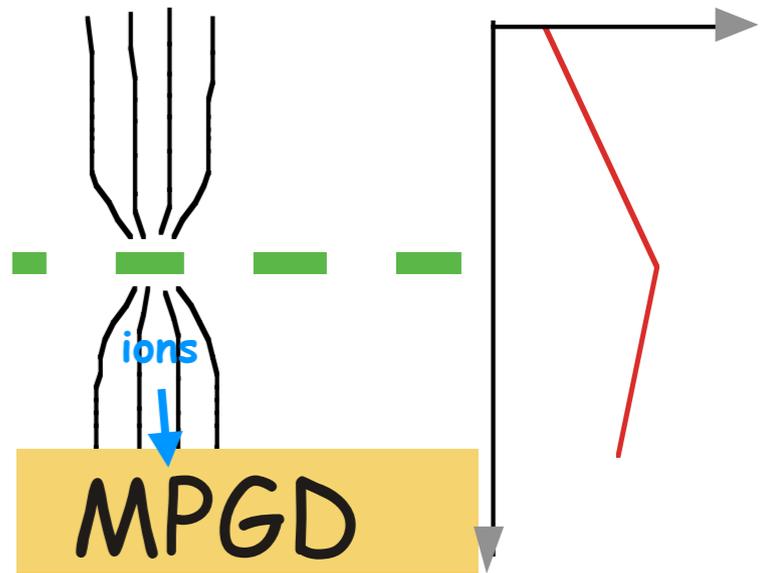
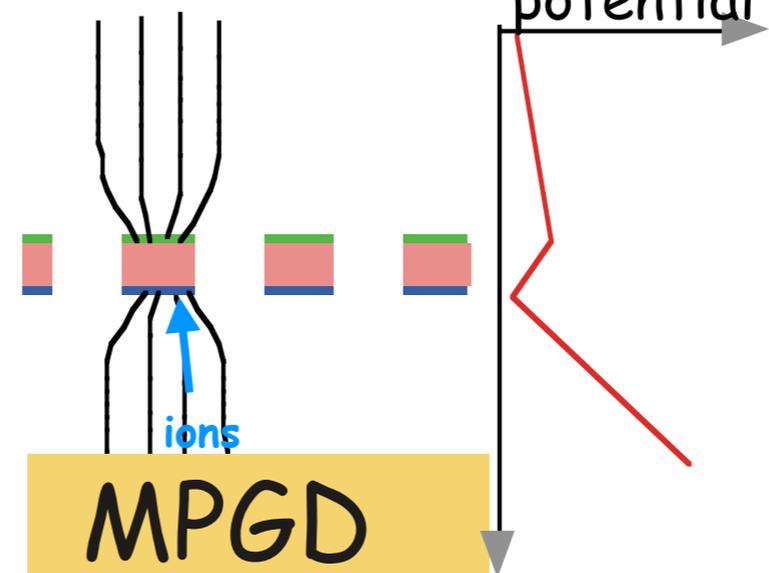
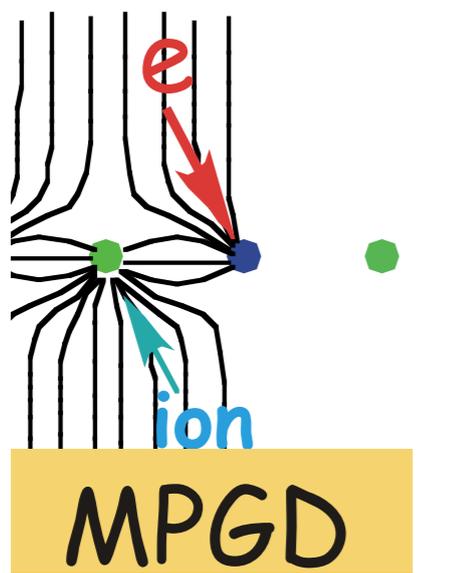
GEM

micromesh

open



close



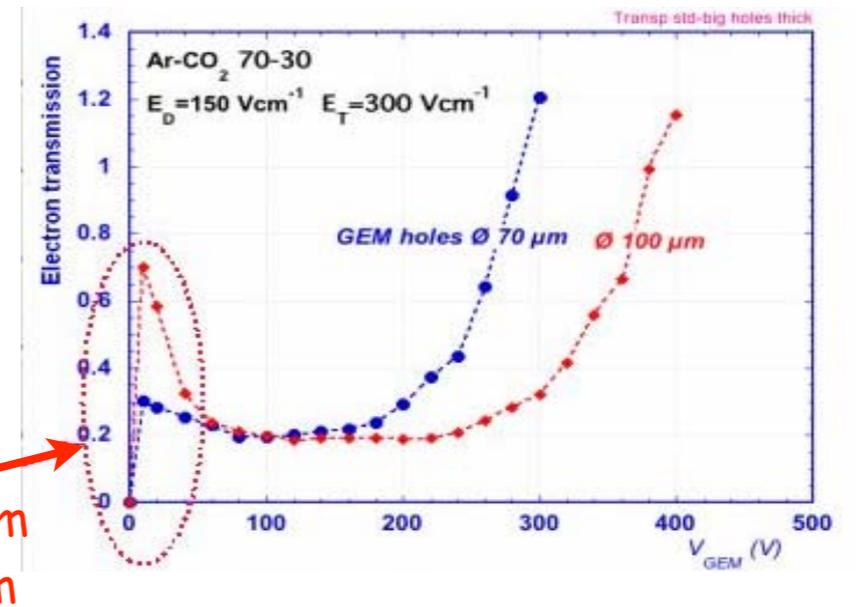
local change of E  
wire tension  
 $E \times B$

local change of E  
electron transmission

change of drift E  
electron transmission

# R&D of GEM type Gate

F.Sauli proposed a GEM as Gating device  
operated at very low voltage at 2006



Realization of GEM Gate is not easy as we thought at the beginning  
due to the limited electron transmission at gate-open.  
especially for high B field !

We realized a necessity of R&D to make a large aperture GEM  
in order to increase electron transmission.

Ordinal chemical etching process can build a 50% aperture GEM  
some challenging company can make a larger aperture but not sure

FUJIKURA investigate process and QC system  
enable to produce GEM with more than 80% aperture  
using laser aviation for insulator removal at 2014

# Gate GEM new vs old

New aperture 80% gate GEM

Old aperture 50% gate GEM

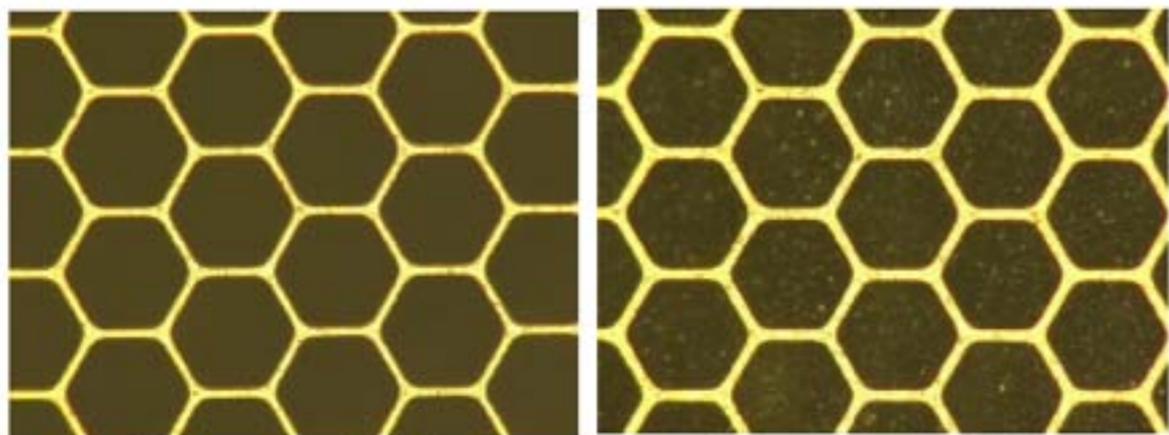
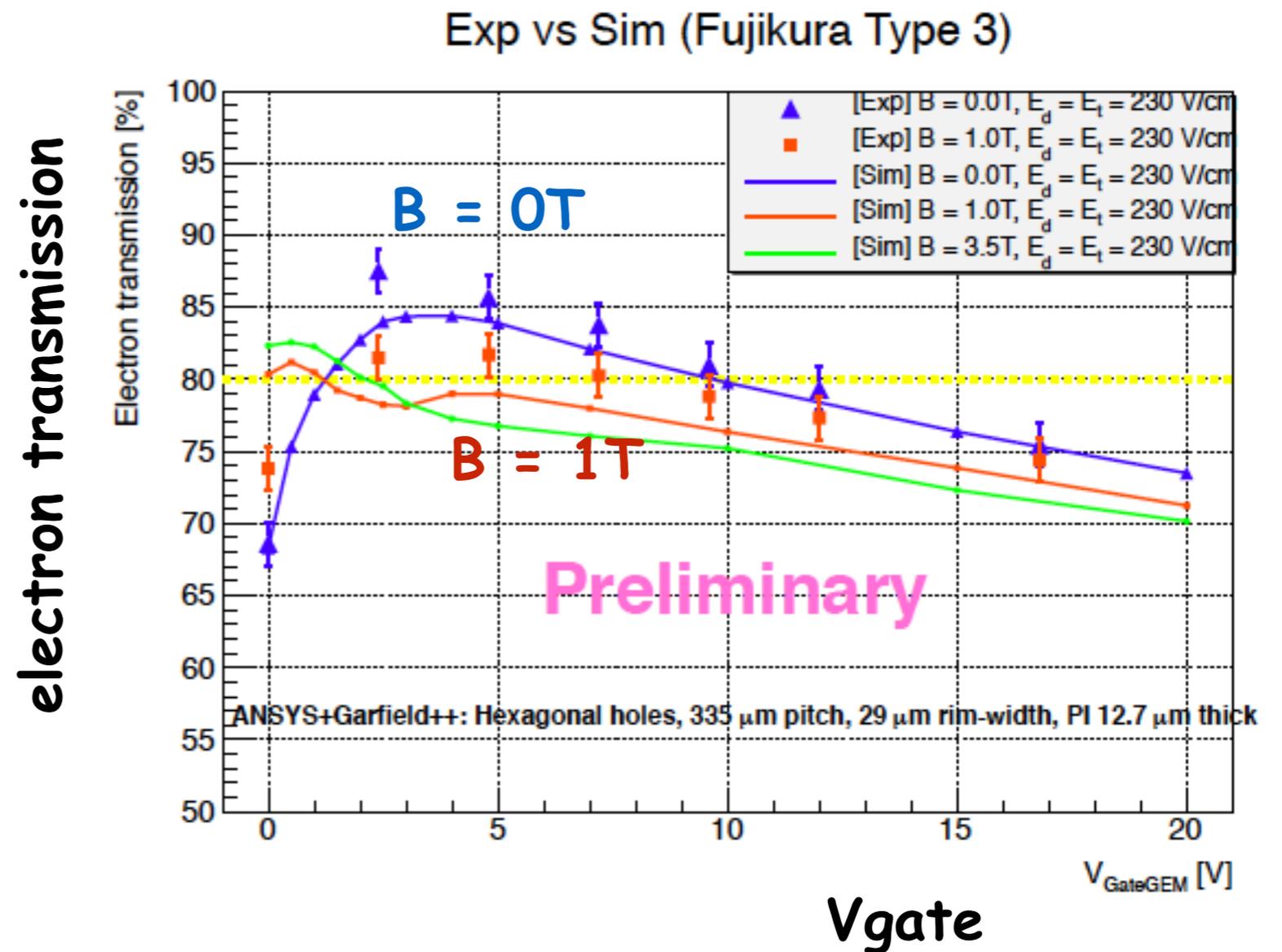


図1. F-side外観

図2. B-side外観

# Electron transmission

10cmx10cm prototype(type 3) provides more than 80% transmission even for  $B = 1\text{T}$  field



module size gate will be tested under LP1 facility using beam on Nov.2016

# R&D of LCTPC

EndPlate and Field cage

Infrastructure of module test (LP1)

module R&D

Asian module, DESY module, Micromegas module

Timepix module

readout electronics/cooling

Distortions

# Endplate

handling/replace --> middle size module

low material : aluminum --> space frame

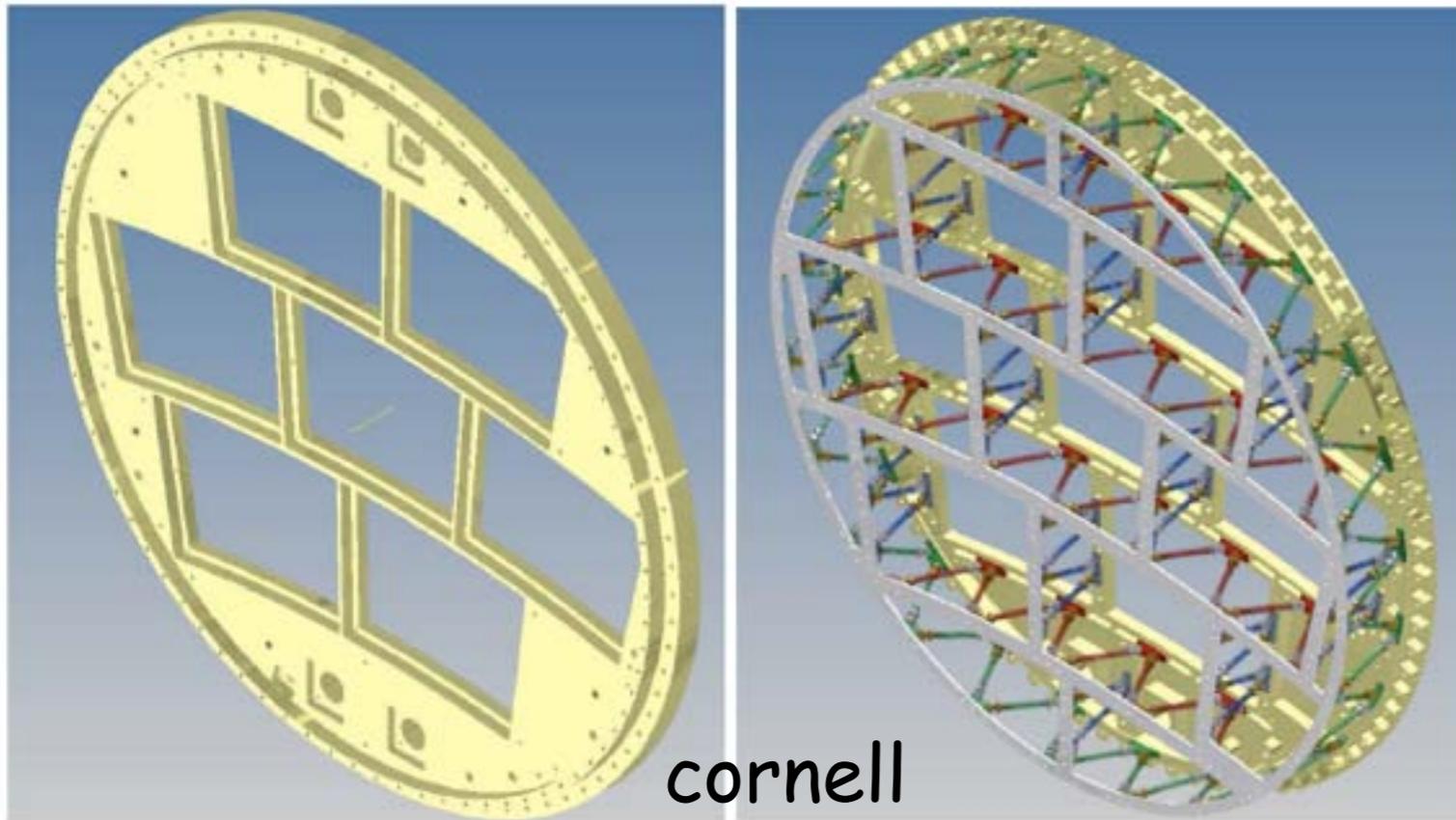
maximize sensitive area

-> install method, module boundary

LP1 endplate ->

will be @ LP2?(1.5)

Field Cage DESY



Double layer Kapton strips  
are laminated on honeycomb cylinder

# LP1 beam-test facility @DESY

## T24 beam line

facility to test various modules  
under the same environments

up to 5GeV/c electron

PCMAG(KEK) provide 1T B field  
on movable stage  
cryo system updated

LP1 field cage fit in the magnet

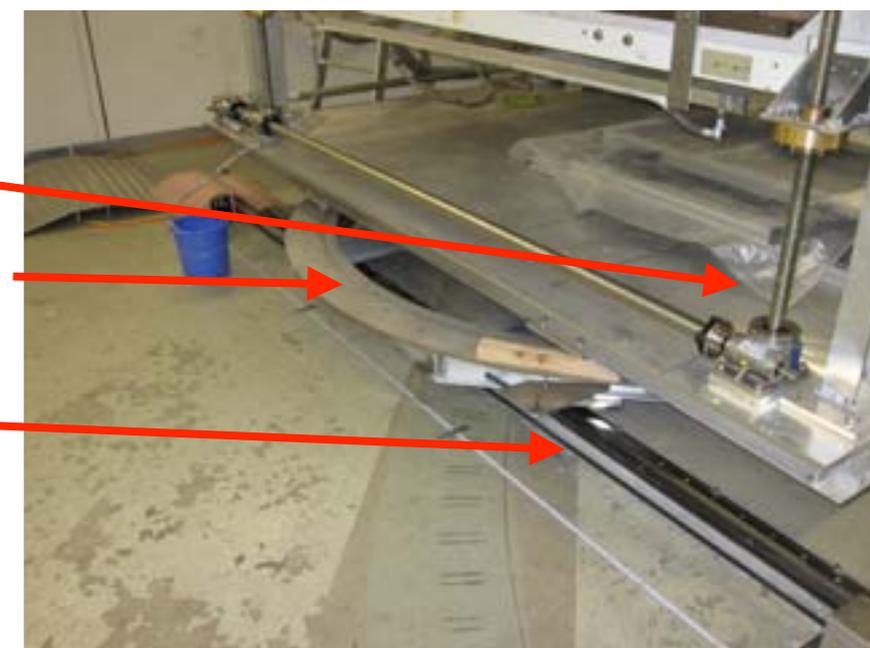
Si tracker was planed to be installed  
in the magnet for precise reference point



y(hight)

phi(turn table)

x(slide bar)

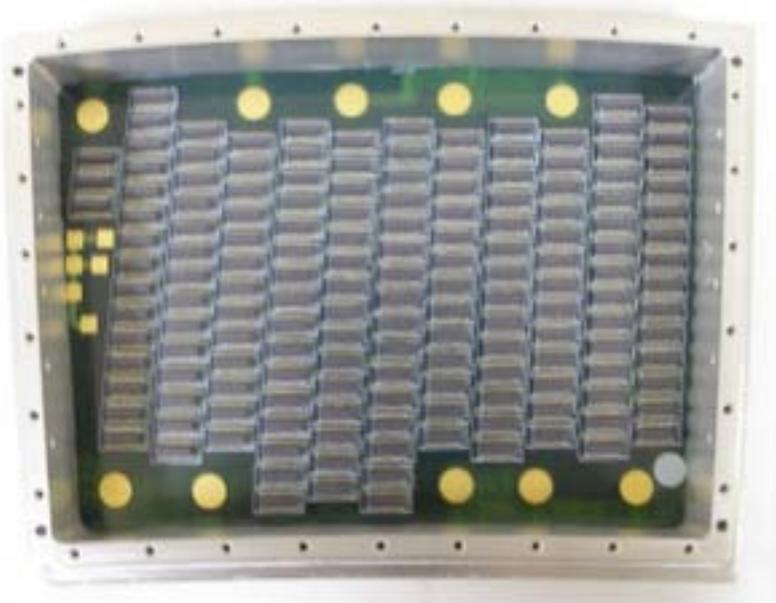
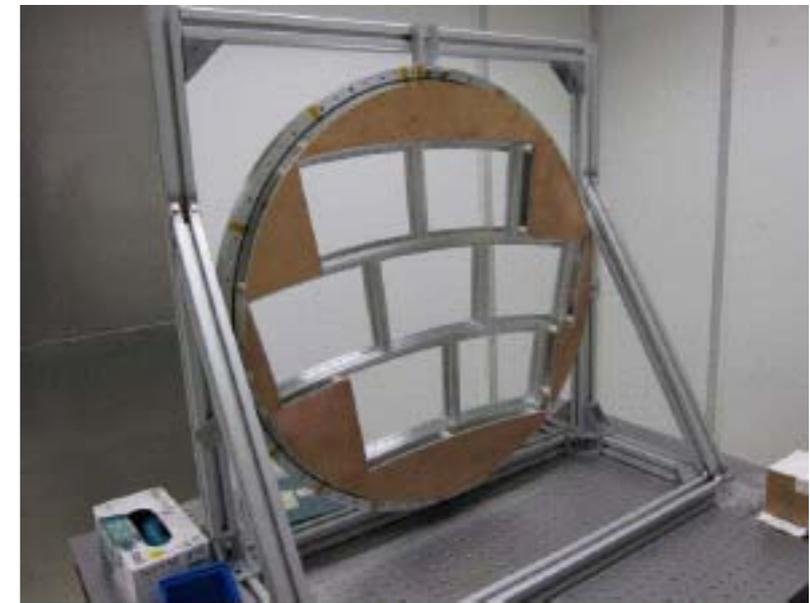


# Concept of Asian module

Minimize insensitive regions  
(module boundary, GEM frame)

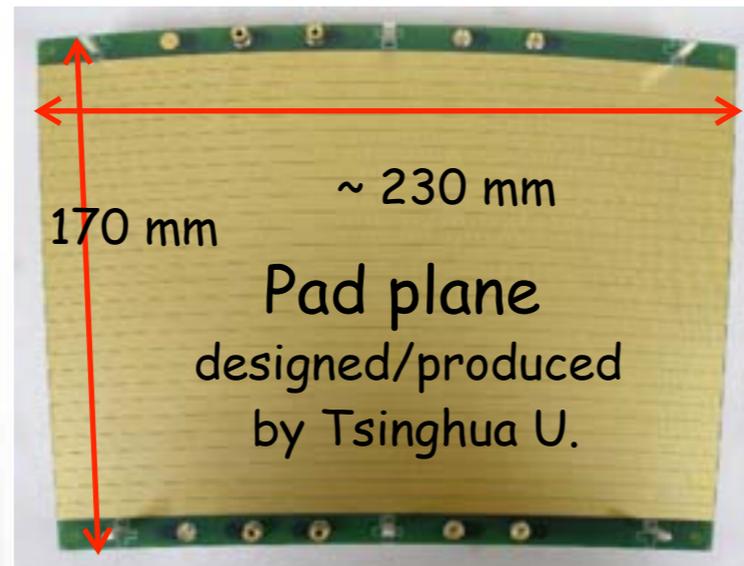
pointing IP

no side frame



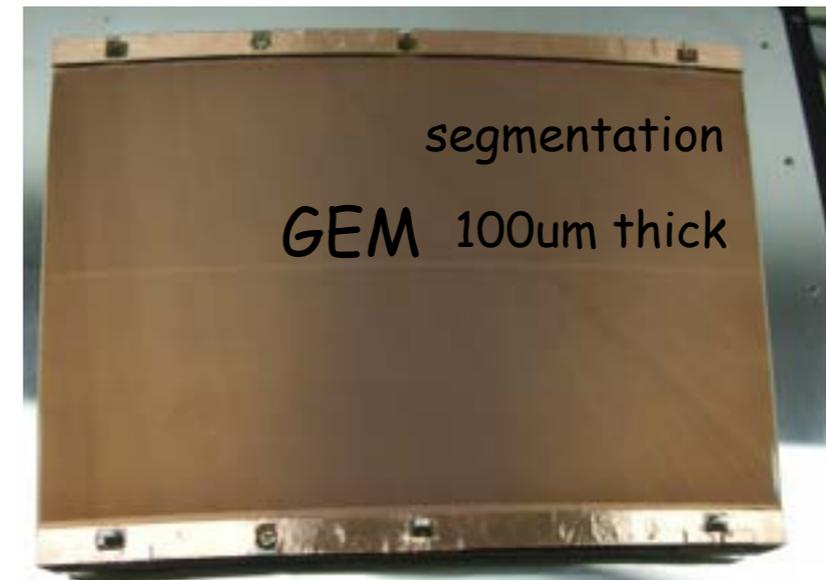
Bunch of tiny connectors  
(40 pins) 161 connectors

all other space for HV supply  
+ Back Frame



28 pad rows (176/192 pads/raw)  
 $\sim 1.2(w) \times 5.4(h) \text{ mm}^2$   
staggered every each layer

Total 5,152 ch/module



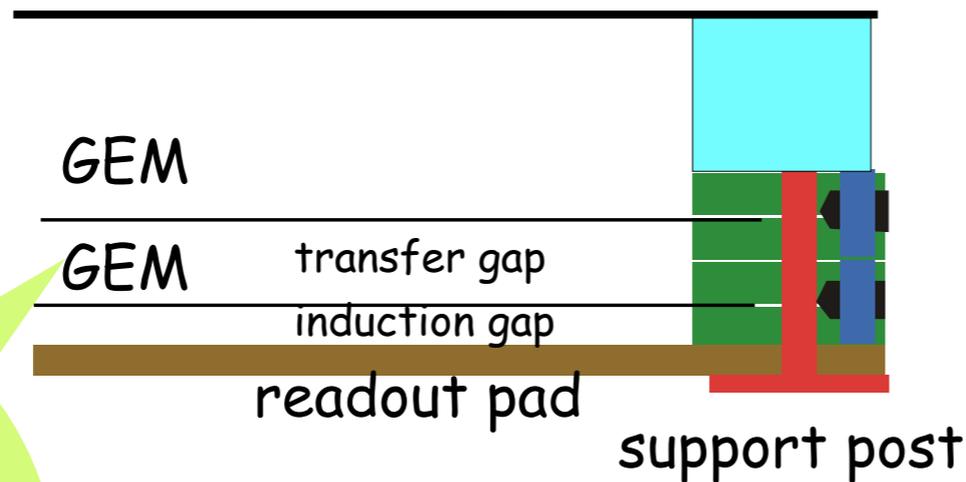
Double GEM (100um thick)  
for simpler structure

GEM electrode is divided in the  
middle of R

**Gate GEM is assumed above GEM structure**

# Asian GEM module

14um Gate GEM

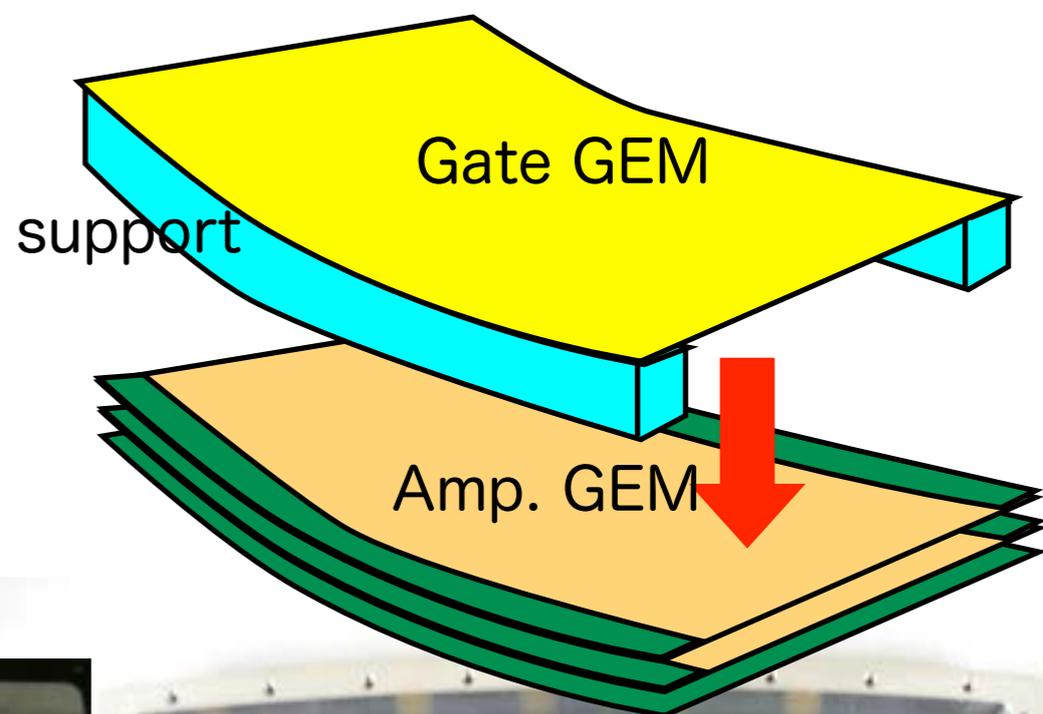
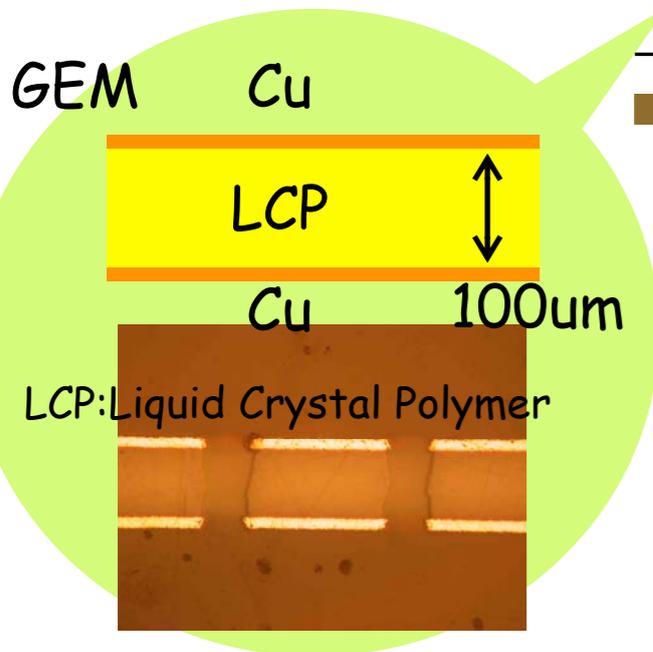


reduce insensitive area pointing to IP  
in  $r\phi$  direction

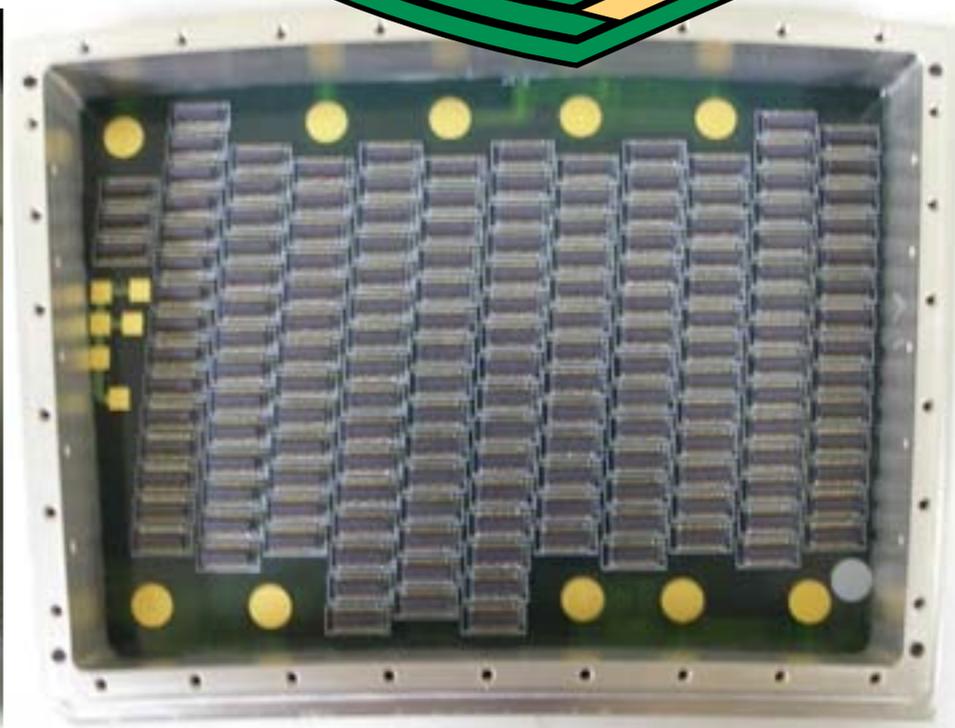
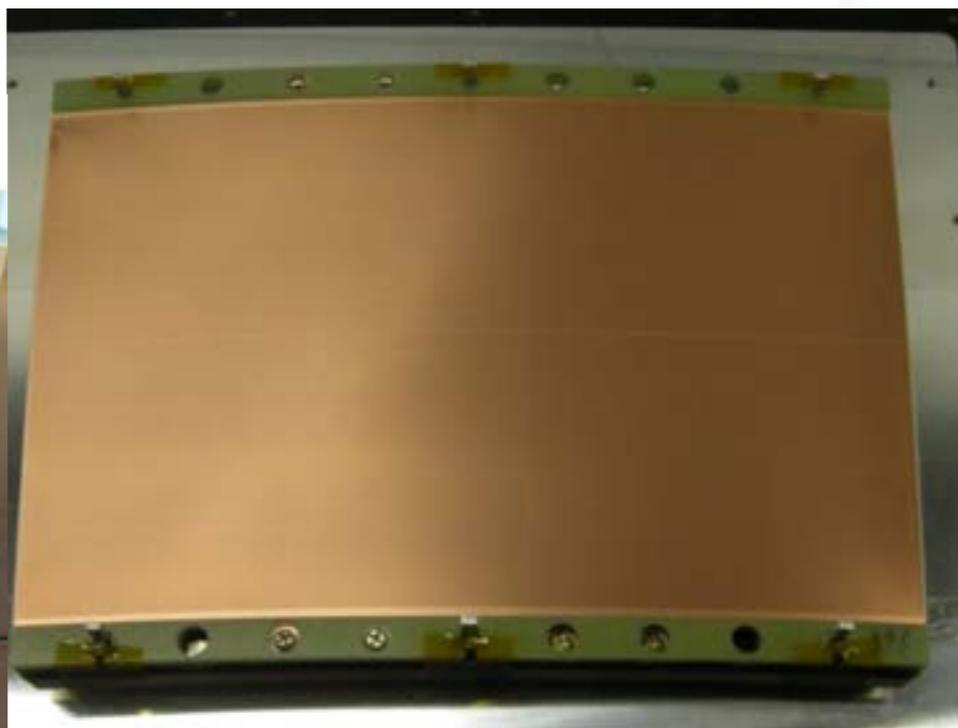
-> side frame less

simplify GEM structure

-> double stuck GEM

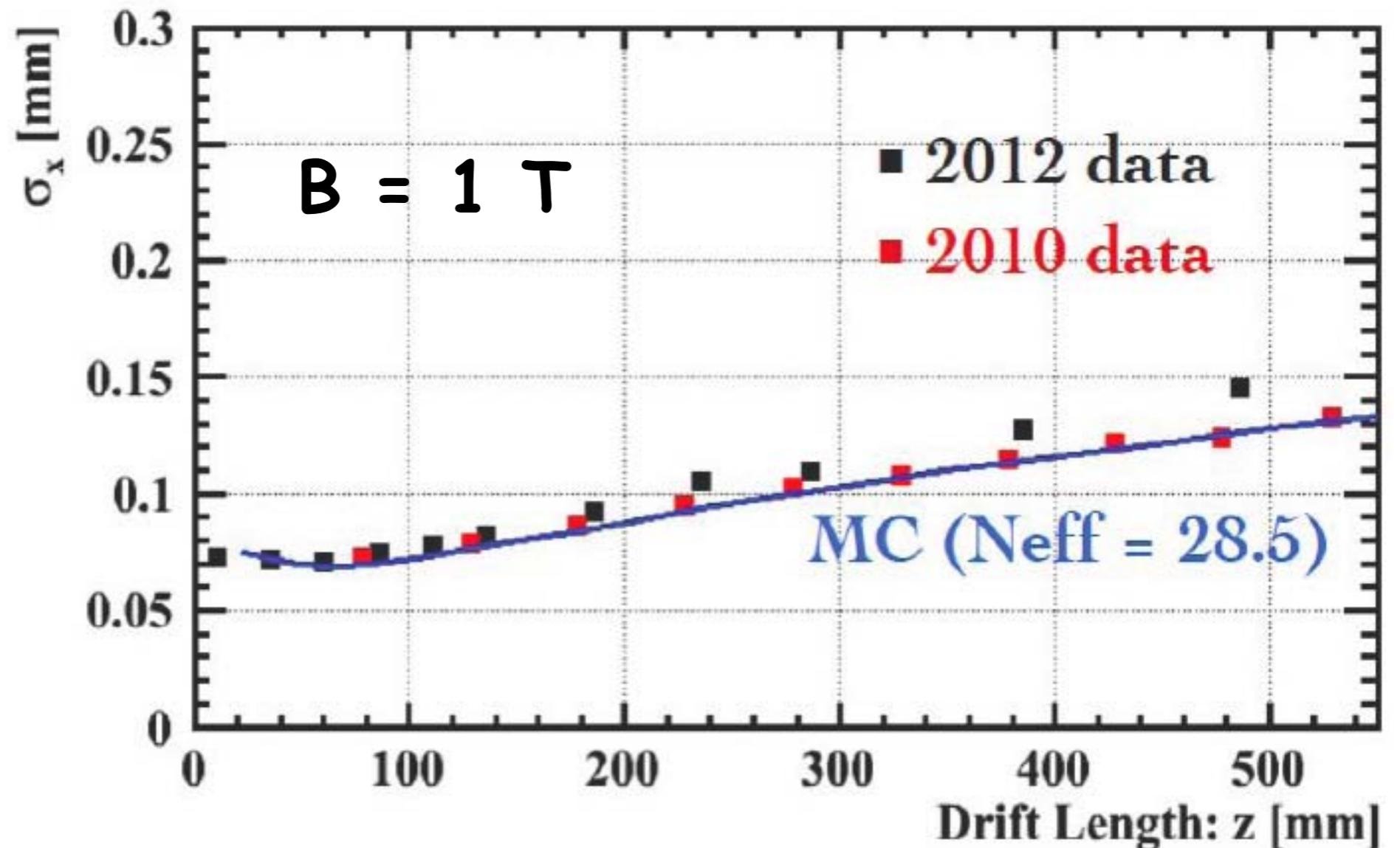


Module installation test with EP2

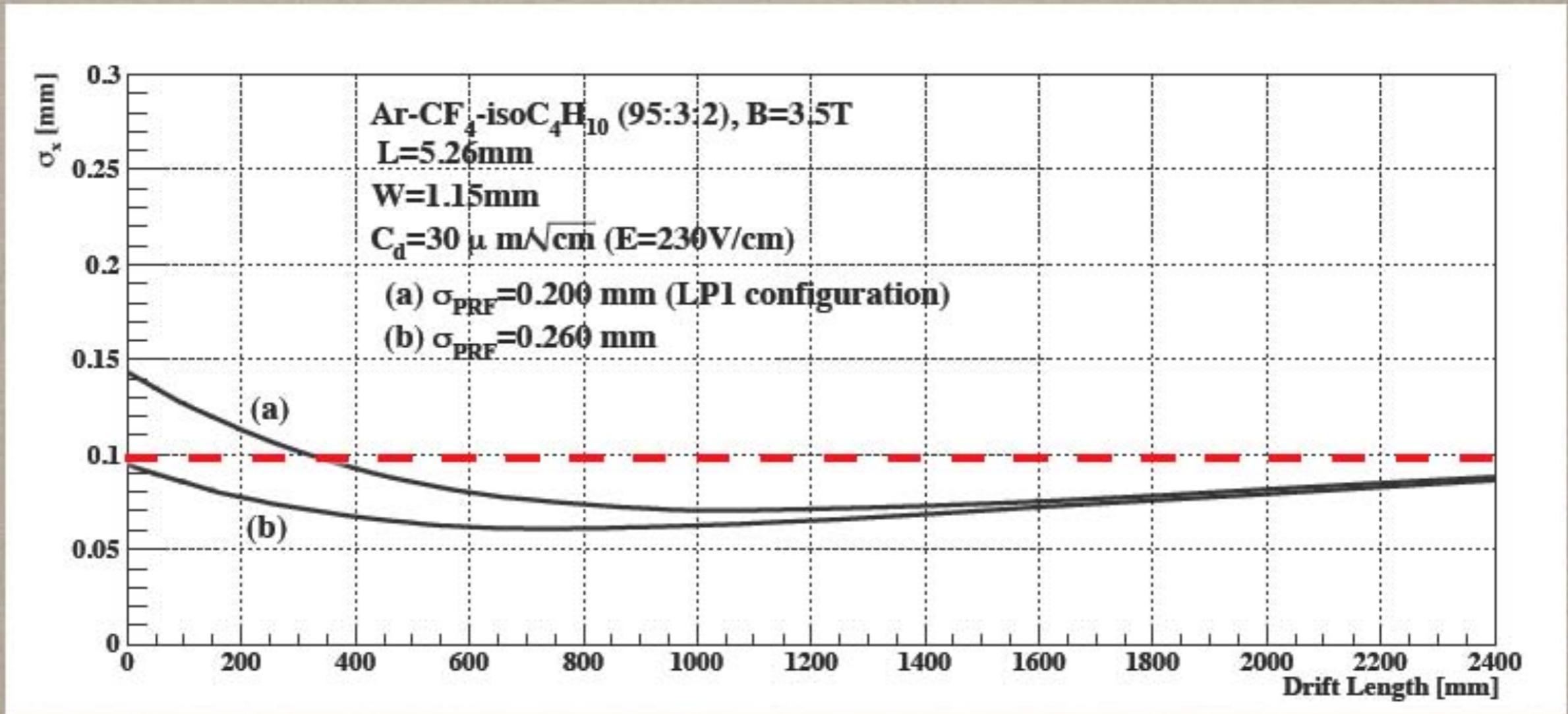


# local resolution as a function of drift distance

central module, row 17



# Extrapolation to the ILD-TPC



**The expect performance is satisfied with the**

In order to achieve 100um res. all over the drift volume, we have to have more diff. @amp region or narrower pad

# Difficulties of module R&D

typical local resolution is as good as we expected

How can we extend this performance to all over the module

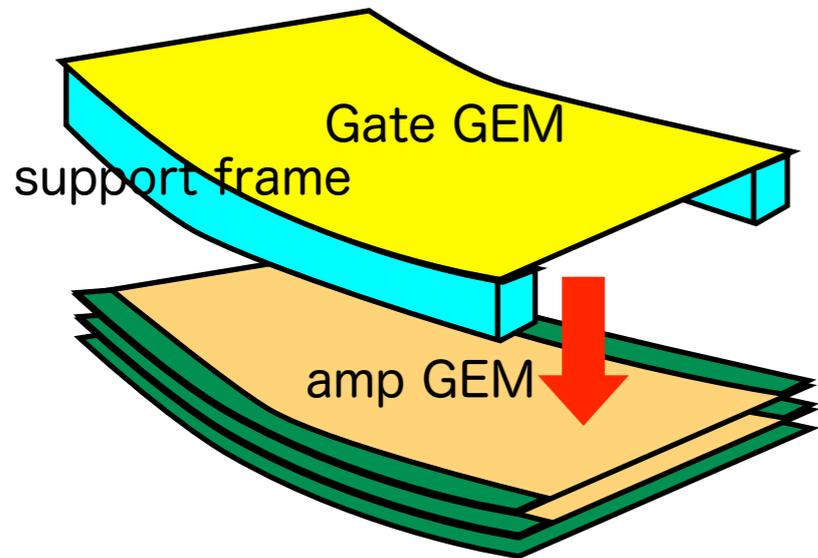
quality of components (GEM, gate, connector.. )

mechanical/engineering (GEM /Gate stretching.....

design

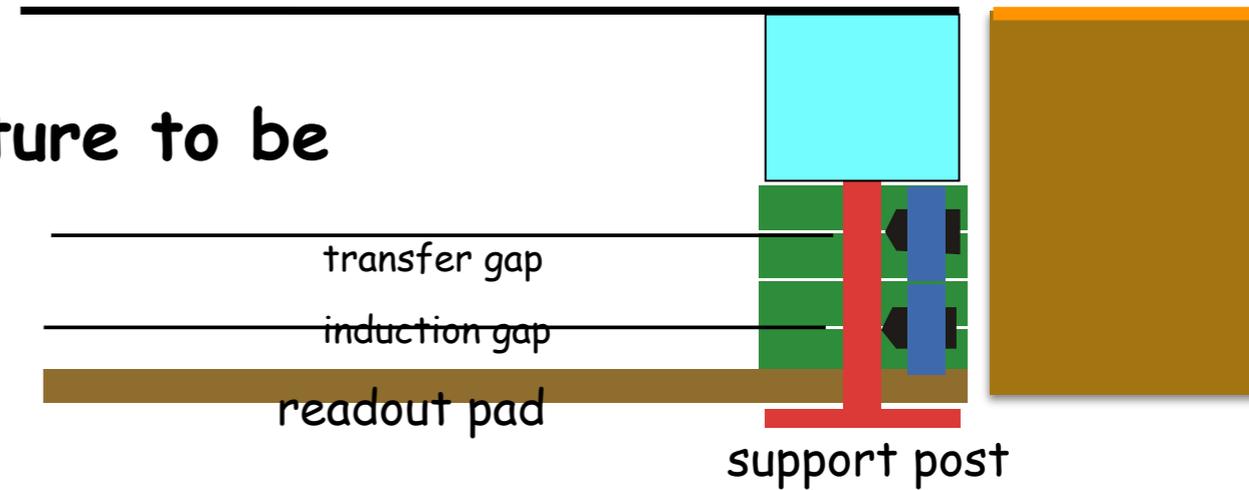
procedure of study

# Design/study process



14um Gate GEM

## Final structure to be

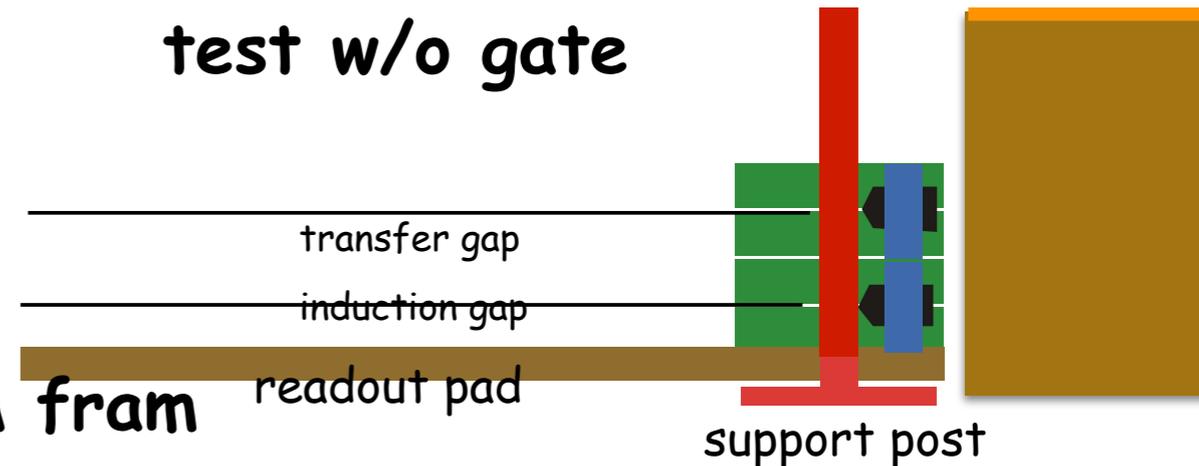


We want to know GEM module performance separating from Gate

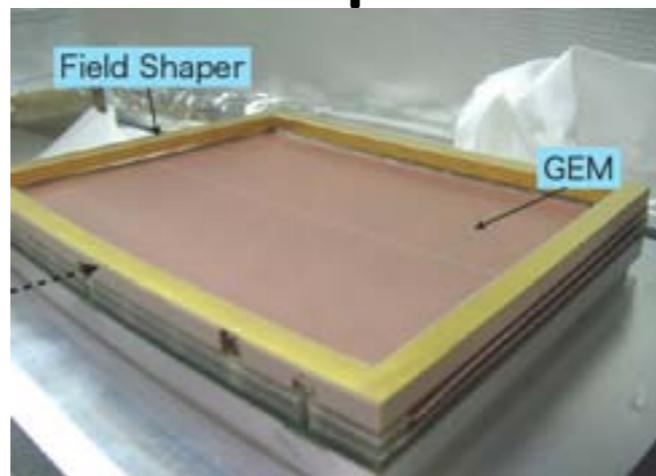
Removal of Gate -> metal post insulated of GEM fram

-> E field is distorted @ boundary

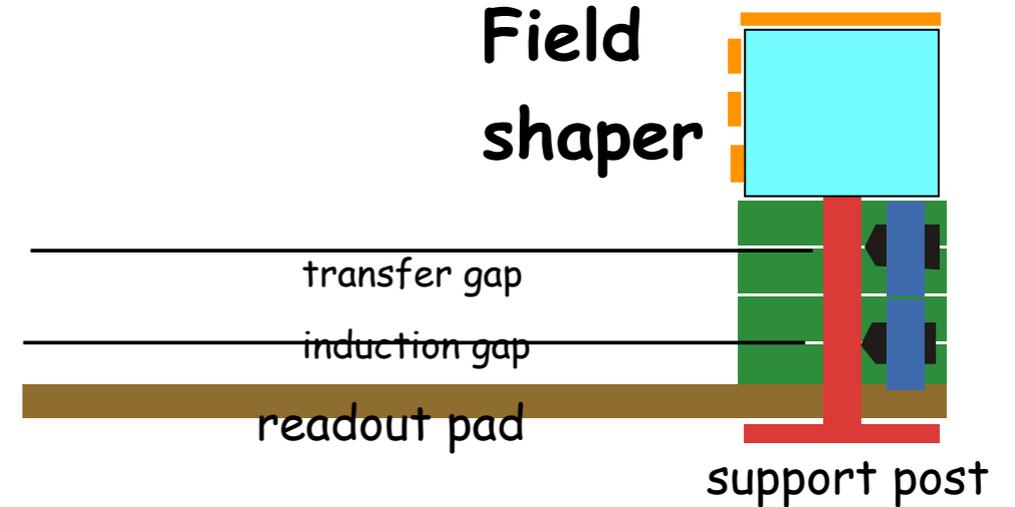
## test w/o gate



Field shaper which cover post and frame

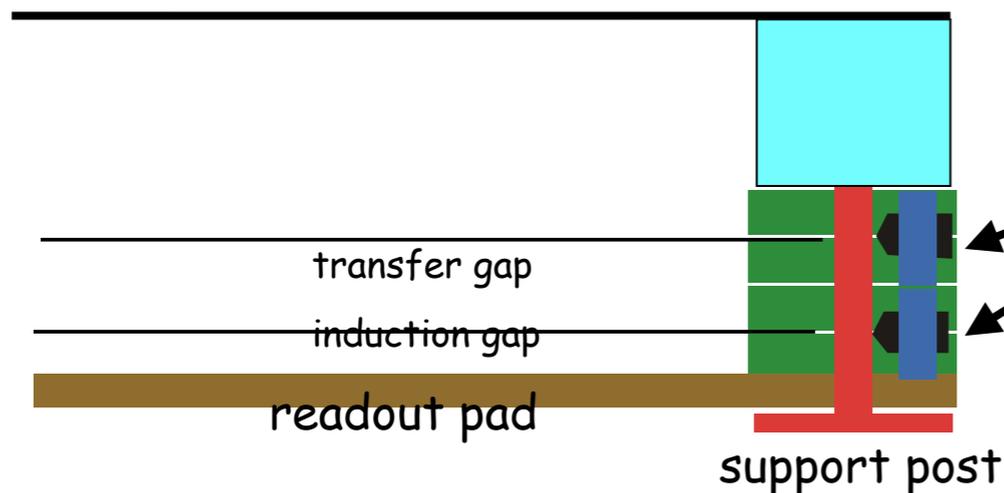


## Field shaper

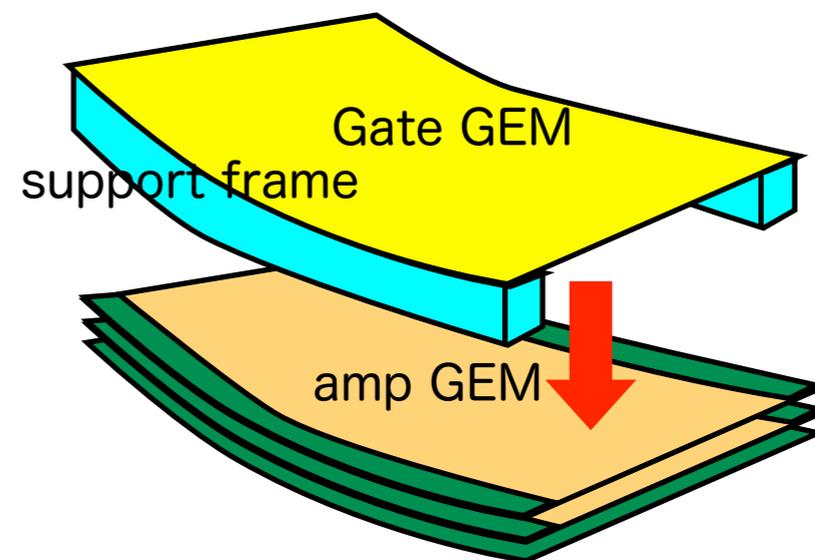


# GEM stretching method

14um Gate GEM



adjusting screw



tension of GEM is applied against post

post by

as mould cost ~10k \$

super engineering plastic

metal post: E field distortion/mechanical dist.

Al

too much room for adjustment

difficult to align GEM on the place

-> shorts to neighbor module

## Lesson

R&D study should be done in step by step:

module design must be cooperated with this procedure

Saving money may not save your R&D

Much room is better than no room but is not proper

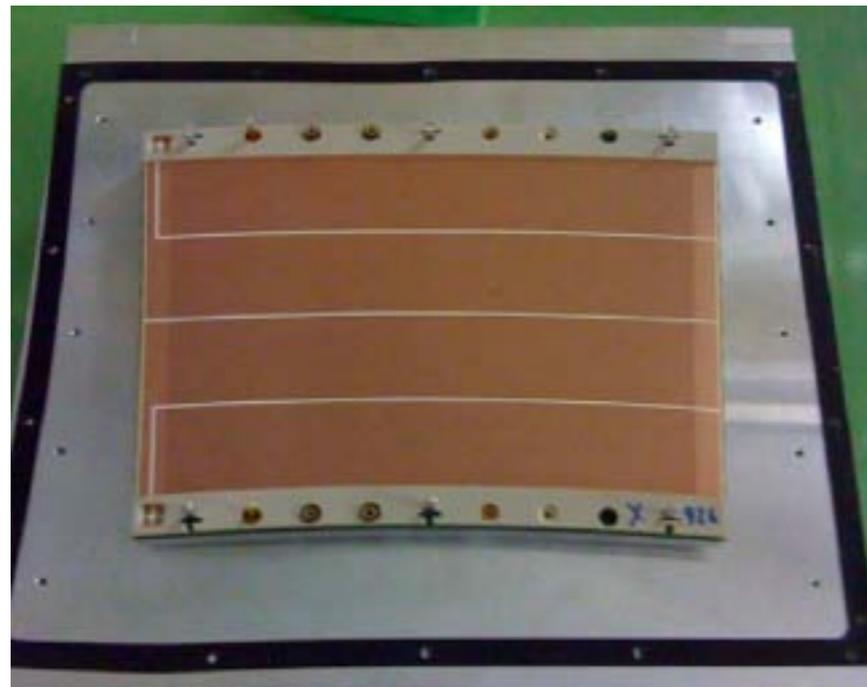
# GEM sheet



segmentation 2

-> observe frequent trip  
gap 300um

-> gap was too short  
one segment trip -> discharge@gap

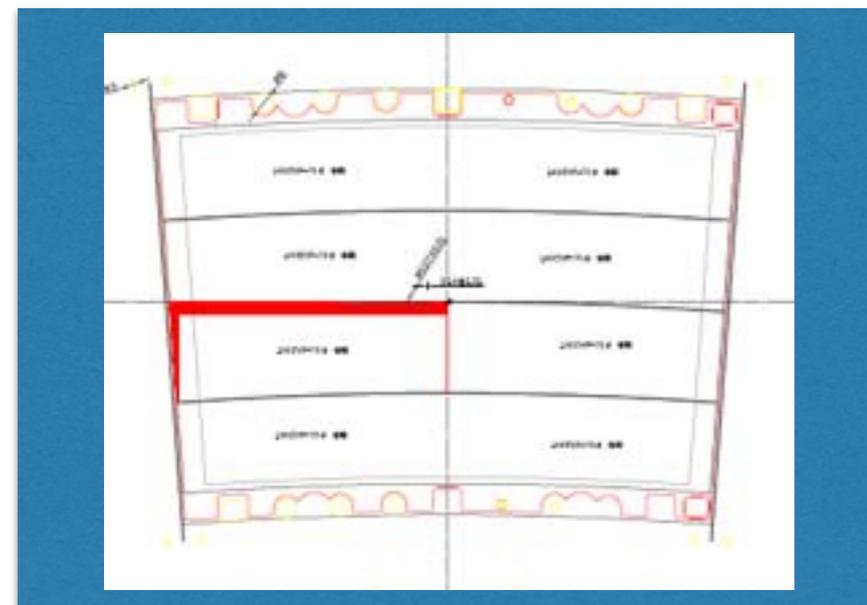


segmentation 4

-> improve? but many discharge  
gap 1mm

-> HV OK but

-> this gap provide another distortion

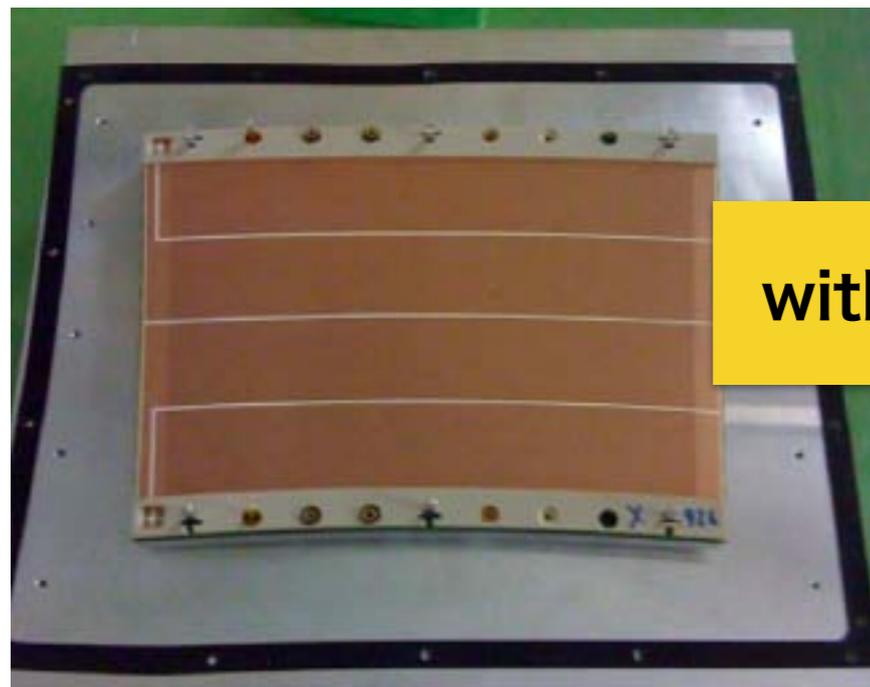


no segmentation@front/ 4 segments@back

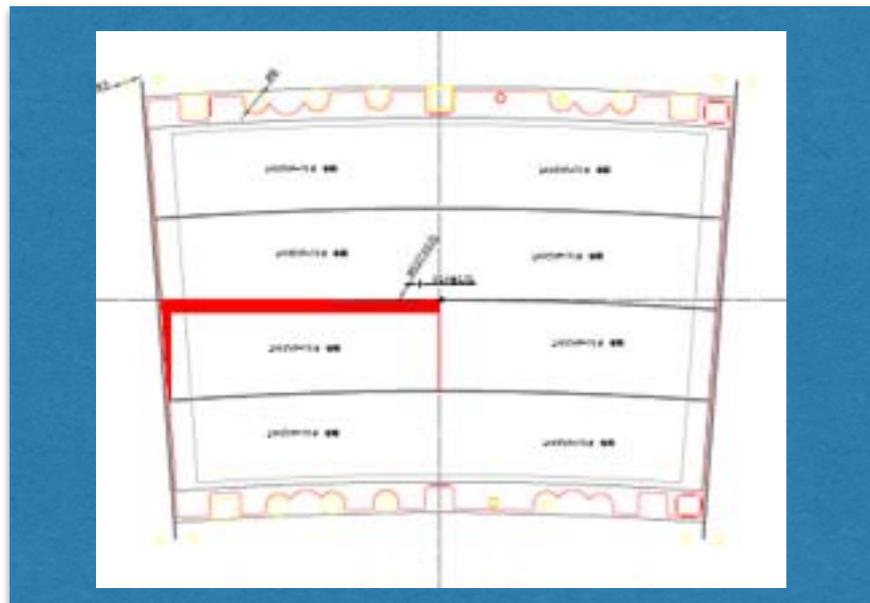
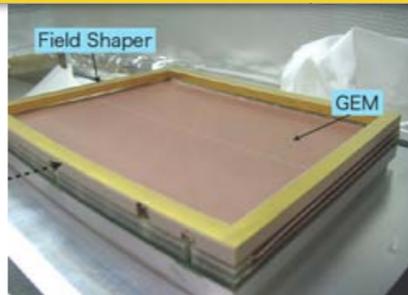
-> distortion became smaller

gap 500um

# GEM sheet



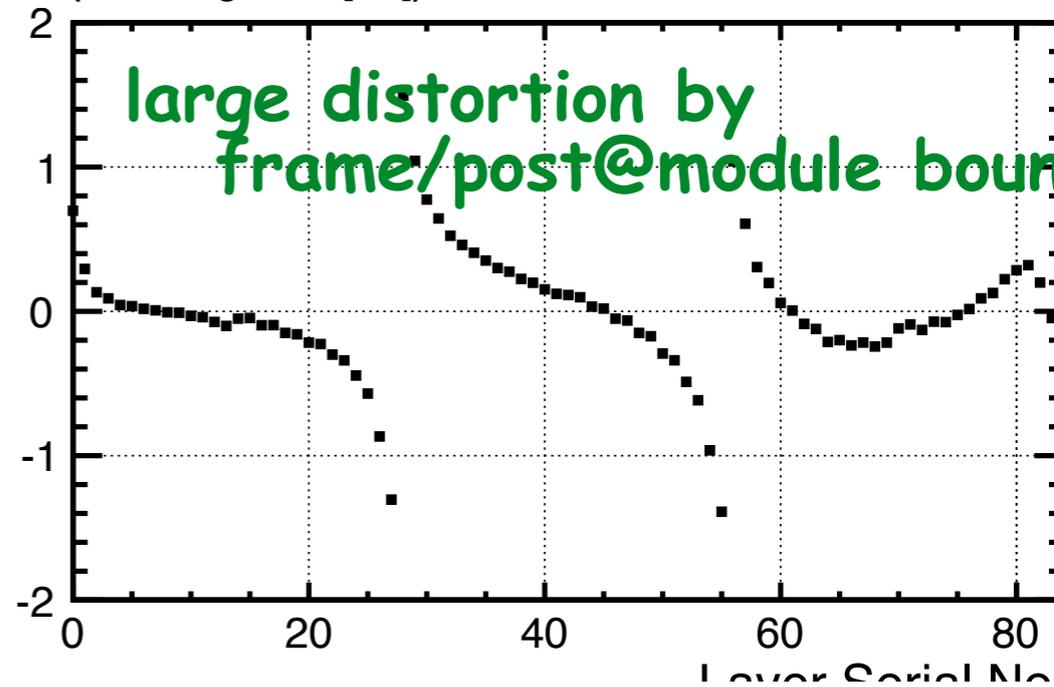
with field shaper



no segmentation  
-> distortion  
gap 500um

$r\phi$  Residual (Drift Length 19.2[cm])

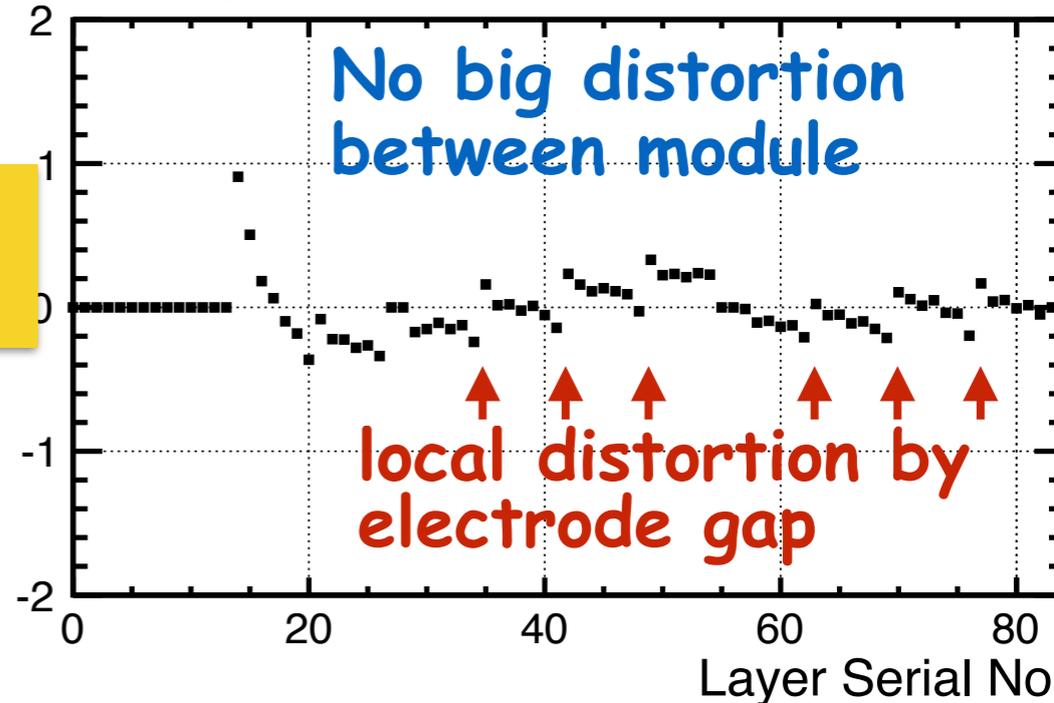
$\Delta(r\phi)$  [mm]



seg

$r\phi$  Residual (Drift Length 20[cm])

$\Delta(r\phi)$  [mm]



beam test on Nov. 2016  
distortion must be much improved

# GEM discharge study

Why our LCP 100um thick GEM discharge frequently ?  
even at reducing GEM segment area

Micro discharge is counted during long term GEM operation  
for 50um(CERN, Raytech, Scienergy) and 100um(Scienergy) GEM  
(standard 10cmx10cm size)

no clear difference was observed

RIKEN group has studied gain stability of LCP GEM  
and found 100% variation even in the same GEM  
due to thickness of insulator (LCP)

LCP: uniformity of thickness is  $O(10\%)$  in specification  
(Kapton/polyimide sheet is much better than this)

## Quality control of GEM

# Next step to realize real TPC

finalize module design

GEM structure, Gate structure, Pad plane

readout electronics

the final RO electronics is postponed until ILC go sign

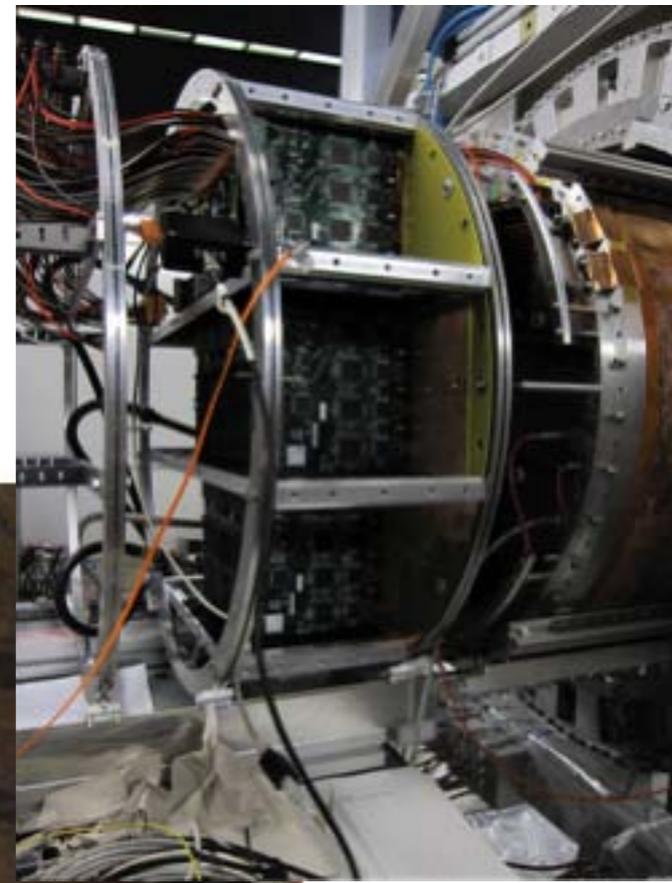
integration of real electronics and cooling

related to Pad plane design

Study is on going with intermediate RO electronics(s-Altro16)

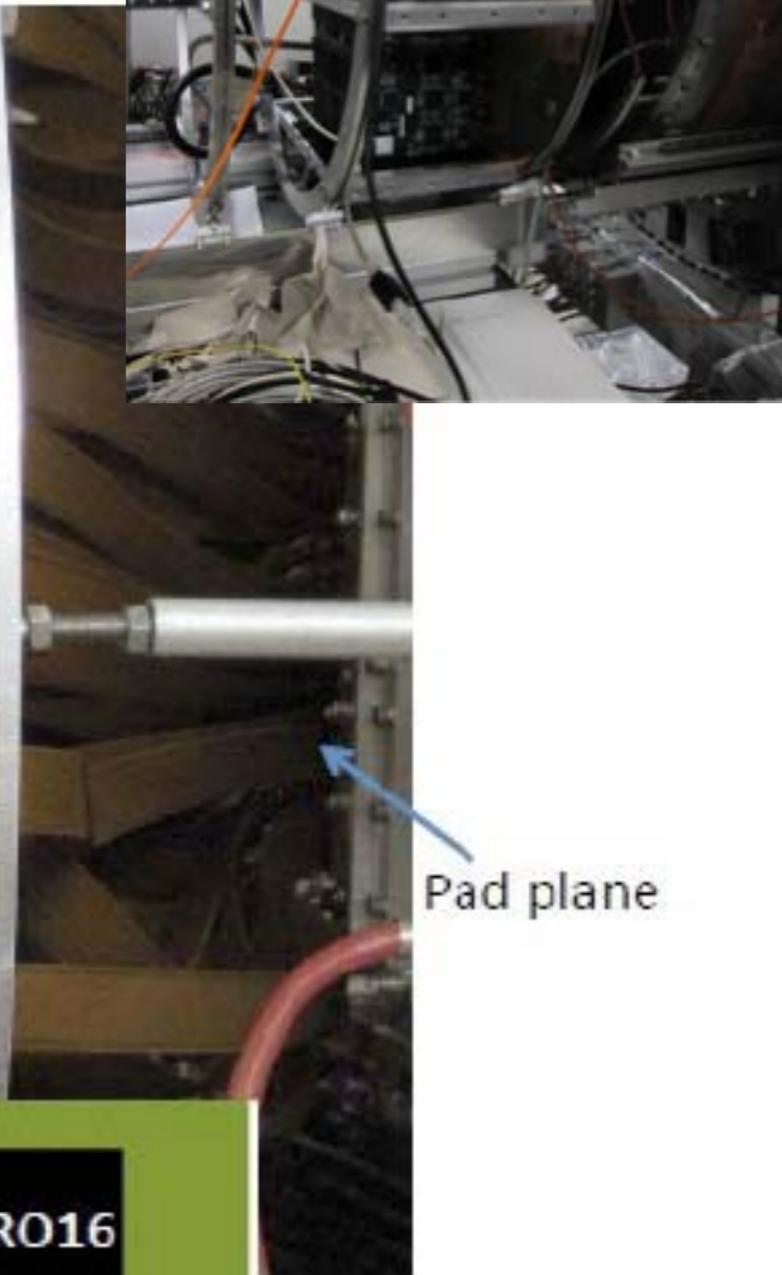
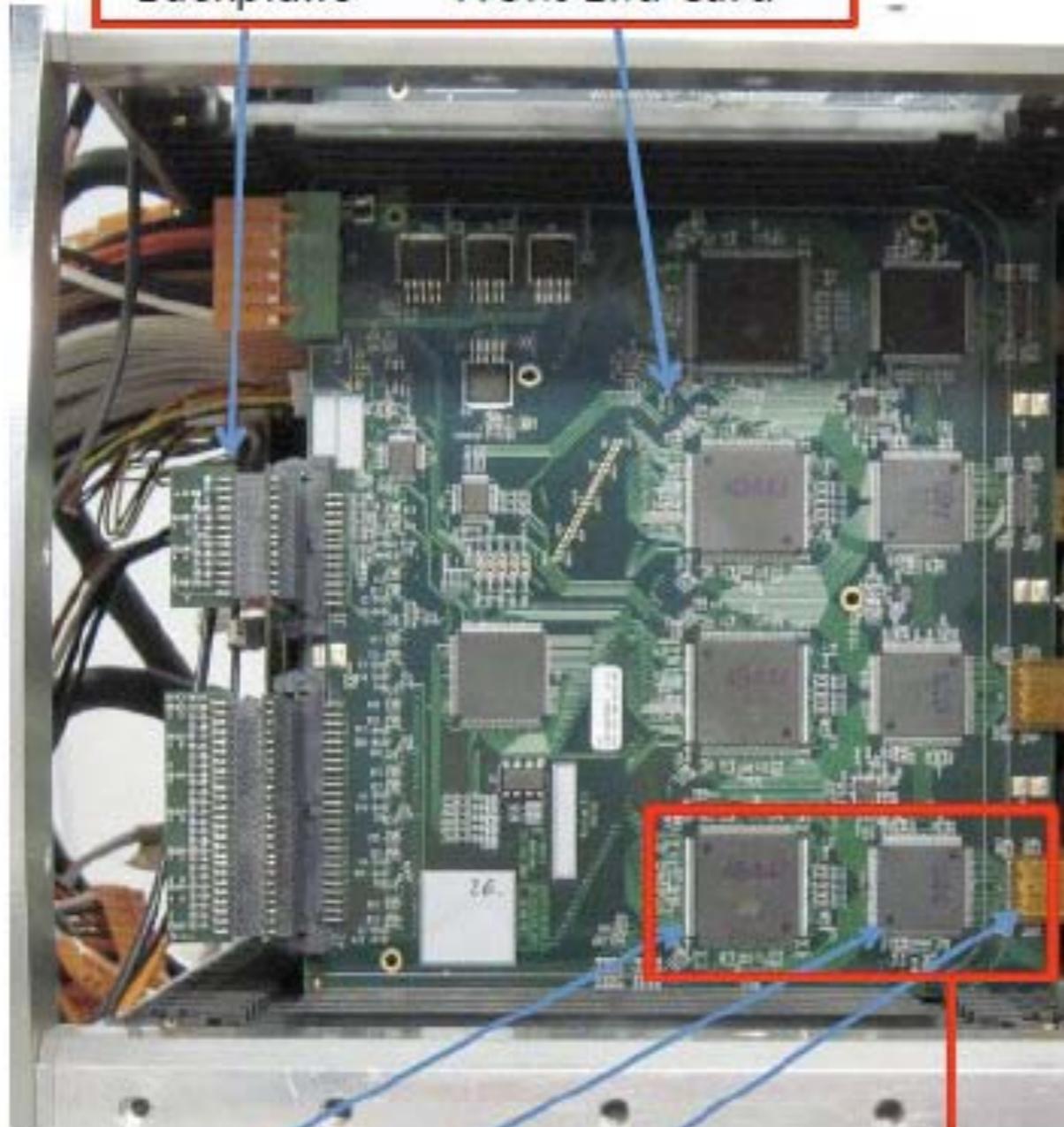
# Integration of PCB+RO electronics @LP1

Present front end electronics  
modified Alice TPC electronics



Backplane    Front End Card

reduction of  
size/material



Pad plane

16 ch ALTRO    PCA16    Kapton cable



MCM  
Multi Chip Module

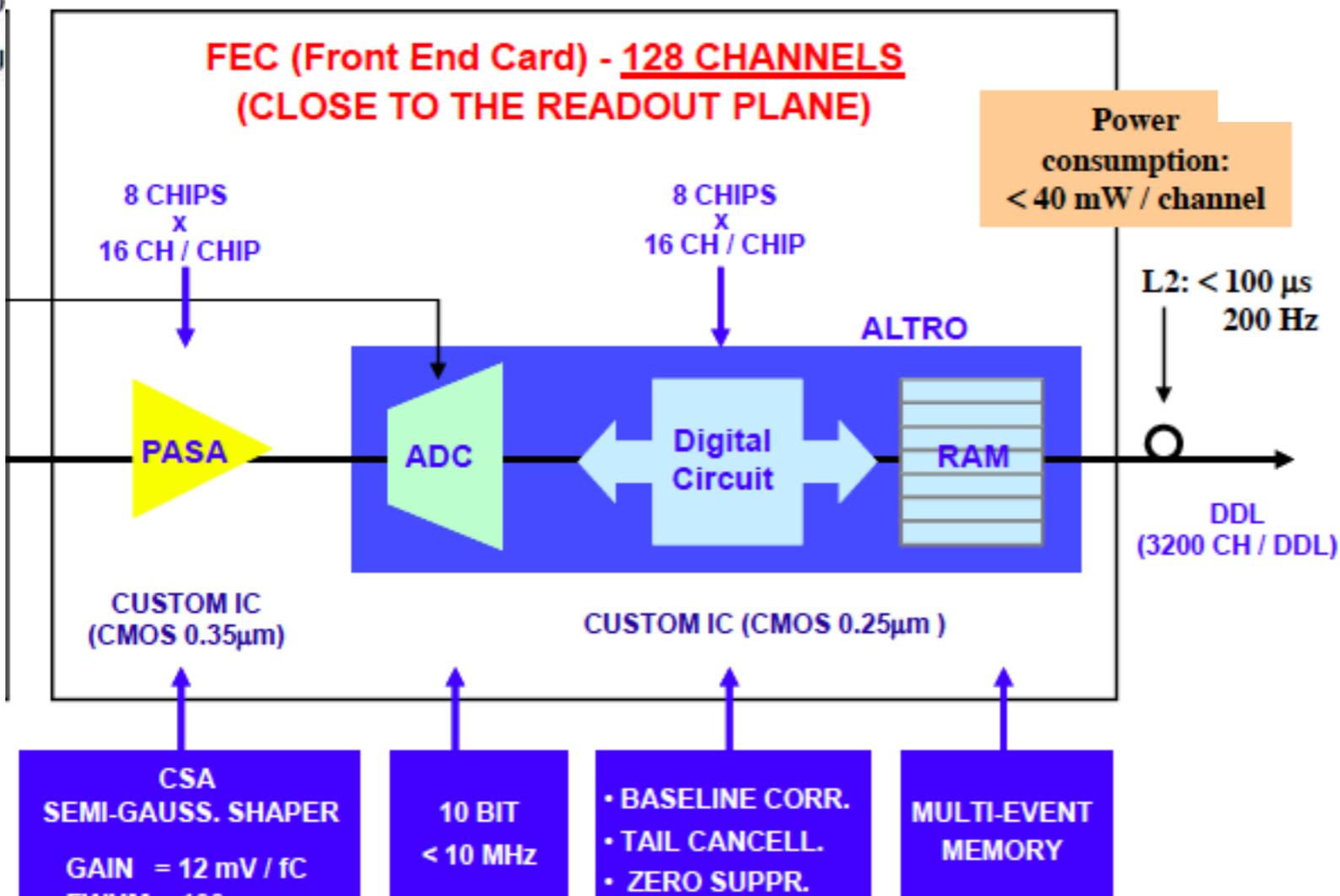
SALTRO16

PAD plane



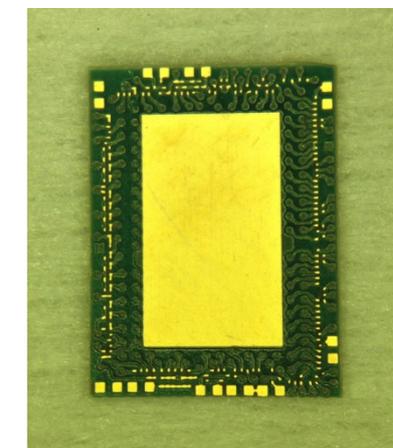
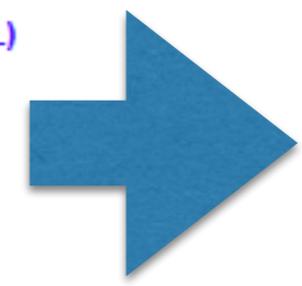
All functions are integrated into one chip: sAltro16 analog-digital mixed

### Front End Electronics Architecture



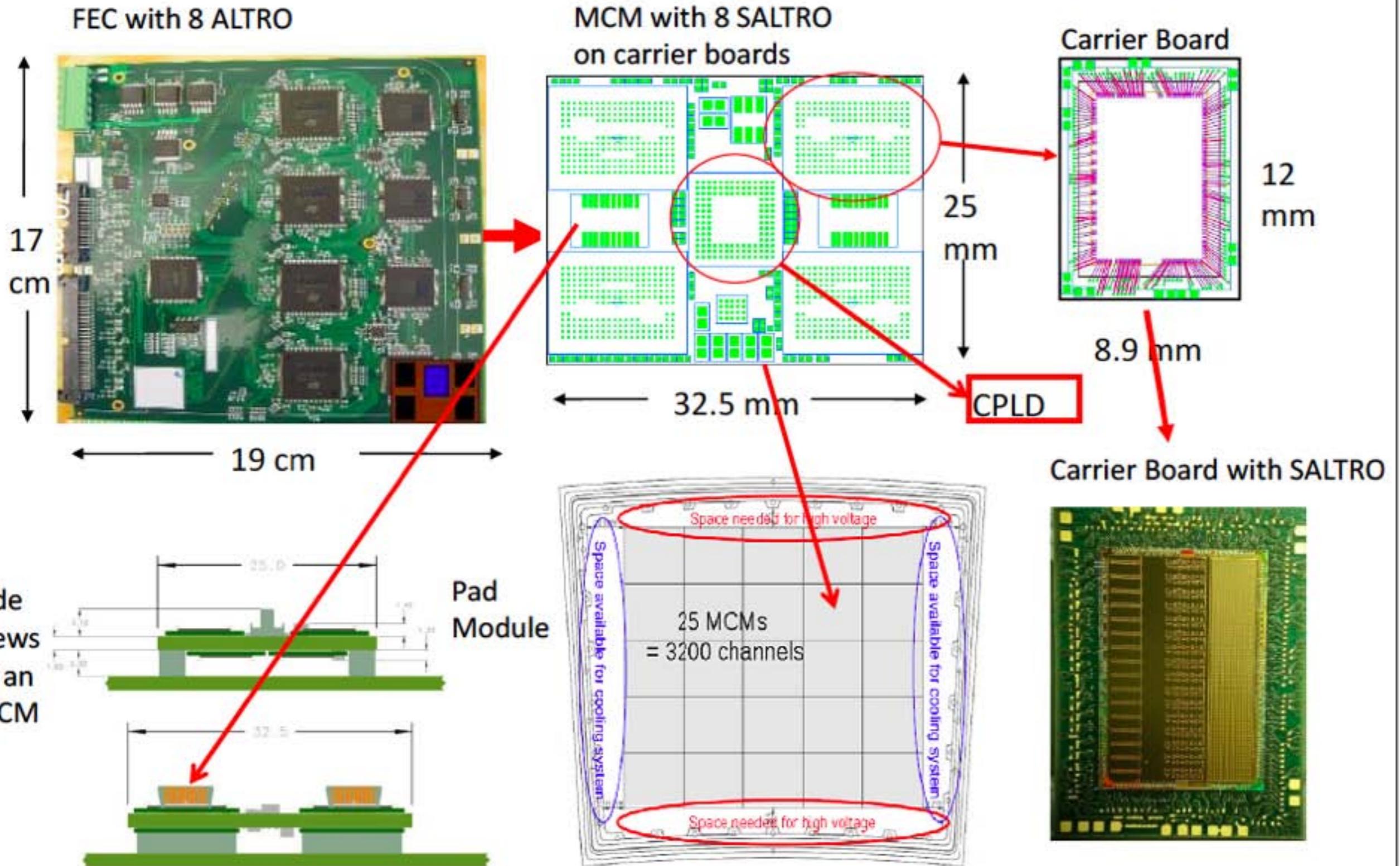
sAltro16 -> sAltro64 extension prog. terminated

But we have many sAltro16 for integration test



# From ALTRO to SALTRO16

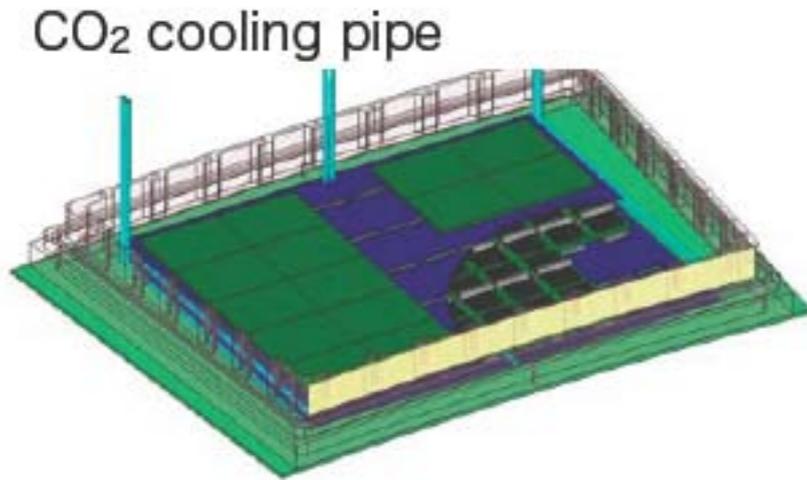
A decrease in size by a factor 40 of the front end electronics



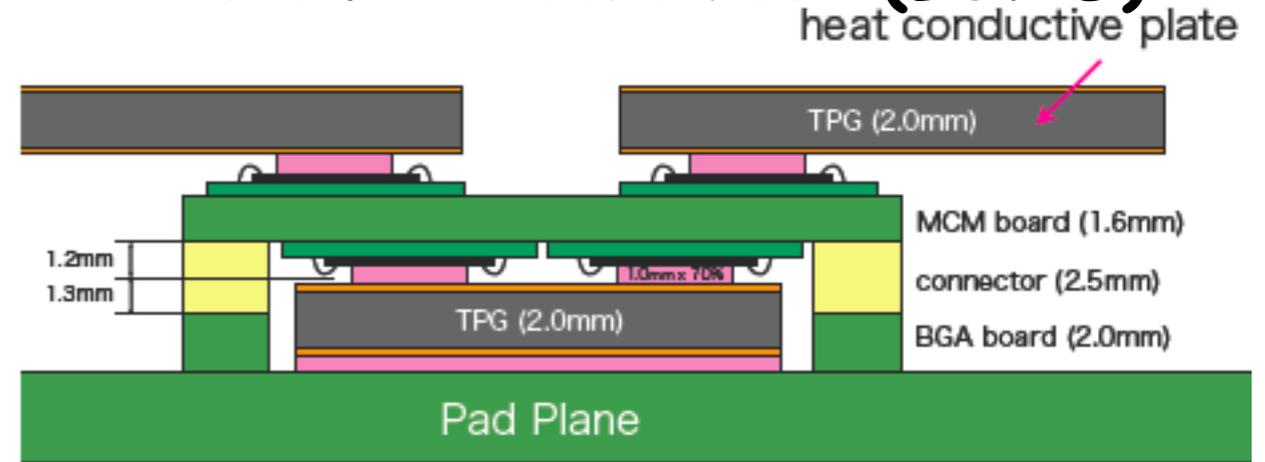
# integration of cooling system

Electronics can be small but power consumption remain same !

Cooling is another important issue



## Readout electronics (LUND)



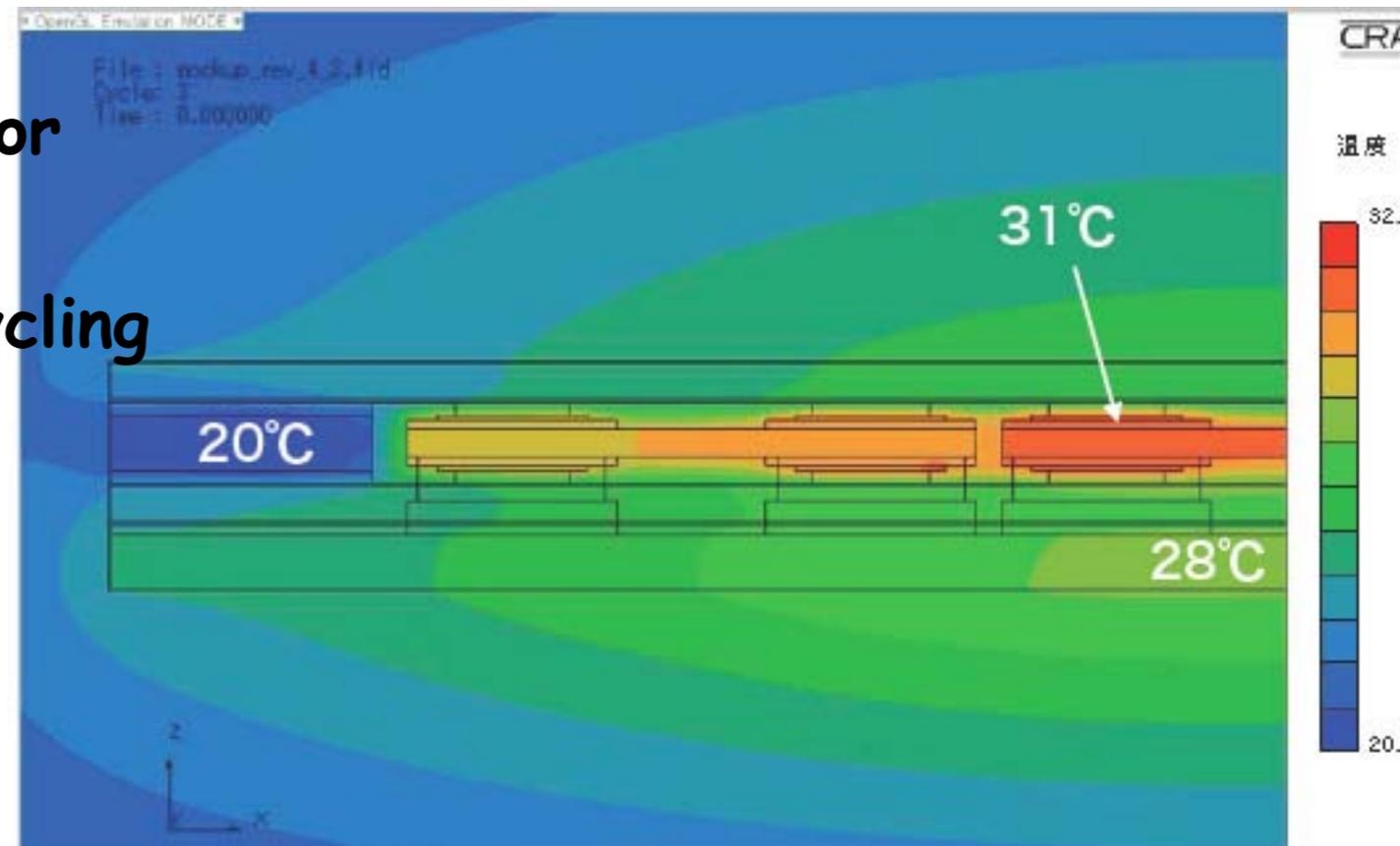
Cooling scheme is studied by Takahiro

simulation using TPG as heat conductor  
non-negligible temp. gradient

w/o power cycling

heat flow through connector

Mockup study is on going



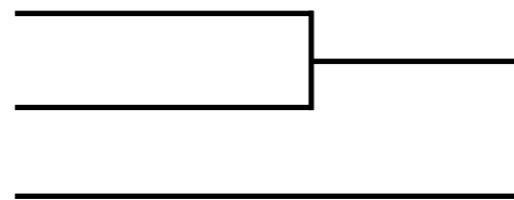
# toward the final module design

3 MPGD modules are studied

Asian GEM module

DESY GEM module

Micromegas module



to LOI

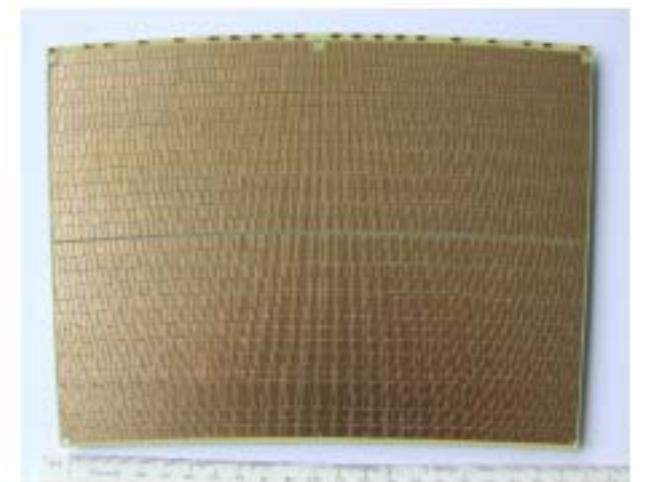
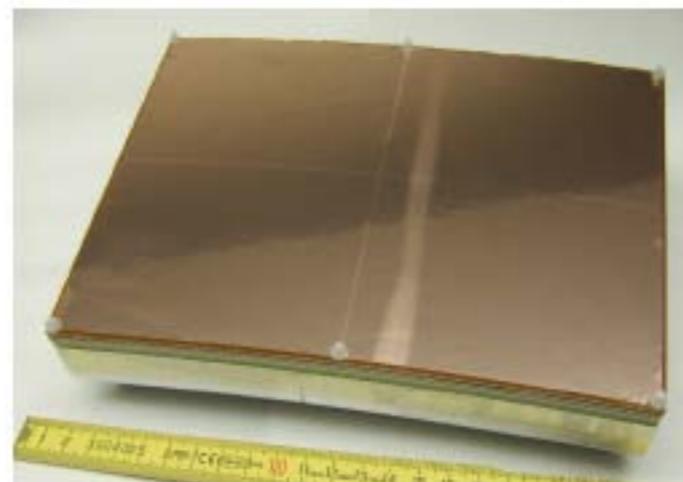
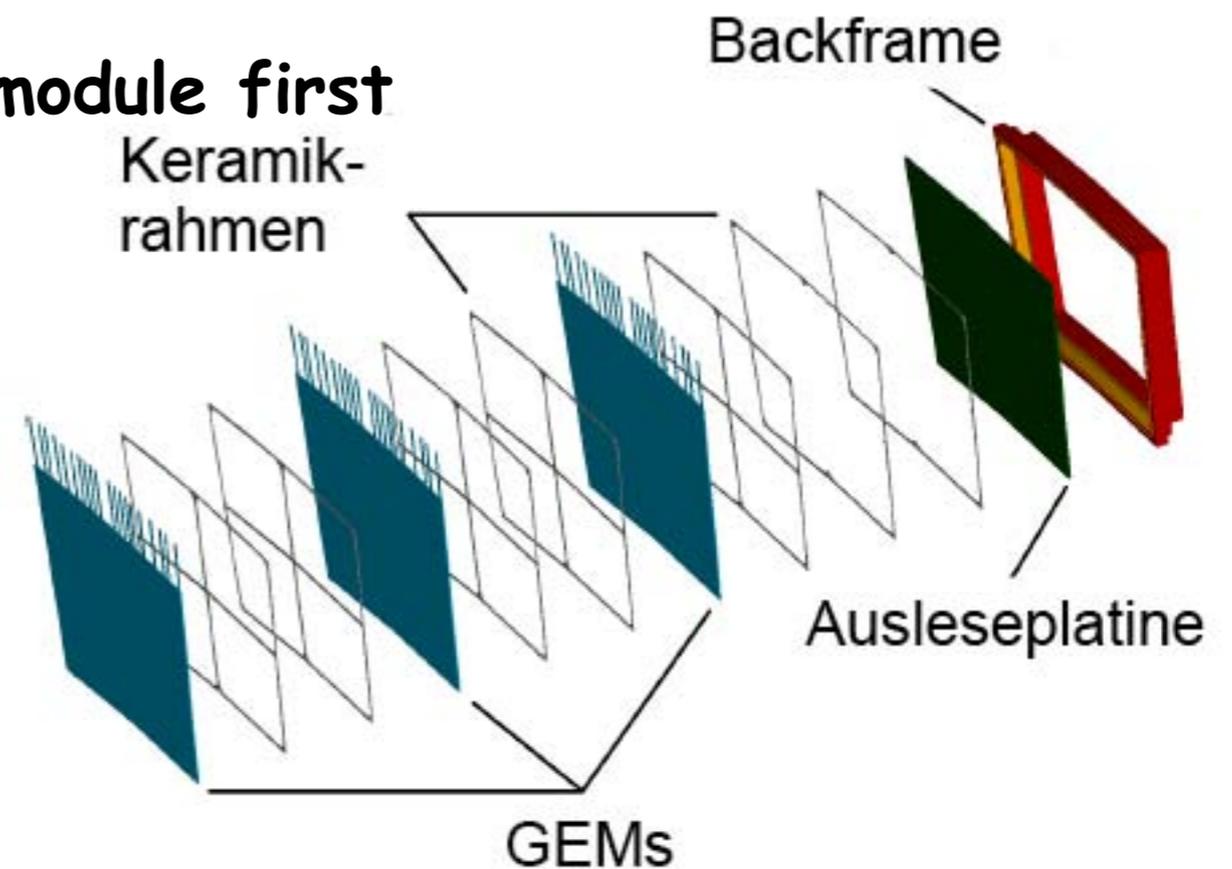
we may need to unify the GEM module first

feature of DESY module

very thin ceramic frame for GEM

triple stack

HV connection



# Summary

GEM Gate seems to be working ( watch the result of next beam test)

We convinced Asian module has a potential to reach to LTPC goal  
100um resolution  
intrinsic performance of each components look OK.

But to achieve ILC requirements over the module/TPC  
improvement of engineering/design/QC are necessary  
design to minimize E distortion